

Program

November 10 (Sunday)

Opening Session

Okinawa Kariyushi Urban Resort Naha 18:00-18:30

Anniversary Section reviewing Widegap Conferences

Okinawa Kariyushi Urban Resort Naha 18:30-19:00

Welcome Reception

Okinawa Kariyushi Urban Resort Naha 19:00-20:30

November 11 (Monday)

Introduction of this Workshop

Auditorium 09:50-10:10

Plenary 1

Auditorium 10:10-11:50

Chair: Tsunenobu Kimoto and Katsumi Kishino

PL-1 (Plenary)

10:10 - 11:00

Materials Designing Novel Wide Gap Semiconductors

Hideo Hosono

Tokyo Institute of Technology, Japan

PL-2 (Plenary)

11:00 - 11:50

Recent progress on the large lattice-mismatched hetero-epitaxy and physical investigation of III-nitride thin films and quantum structures

Bo Shen

Research center of wide bandgap semiconductors and the State key laboratory of artificial microstructures and mesoscopic physics, Peking University, China

Poster Session A

Tunnel Gallery 11:50-13:40

MoP-GR-1 (Poster)

11:50 - 13:40

HVPE GaN Growth using Hydrogen Radical

Mei Kanda* and Hiroshi Nagayoshi

Department of Electronic Engineering, National Institute of Technology, Tokyo College, Japan

MoP-GR-2 (Poster)

11:50 - 13:40

The Electronic Structure of Dislocation in GaN with Mg Impurities

Takashi Nakano,^{*1} Yosuke Harashima,² Kenta Chokawa,² Masaaki Araidai,^{1,2} Kenji Shiraishi,^{1,2} Atsushi Oshiyama,² Akira Kusaba,³ Yoshihiro Kangawa,^{2,4} Atsushi Tanaka,² Yoshio Honda,^{1,2} and Hiroshi Amano^{1,2}

¹Graduate School of Engineering, Nagoya University, Japan, ²Institute of Materials and Systems for Sustainability, Nagoya University, Japan, ³Computer Centre, Gakushuin University, Japan, ⁴Research Institute for Applied Mechanics, Kyushu University, Japan

MoP-GR-3 (No Show)

11:50 - 13:40

Epitaxial growth of high quality GaN layer on boron nitride nanotubes as intermediate layer

Gun Hee Lee,¹ Chil-Hyoung Lee,² Jae Won Jeong,² Su Jin Kim,² Eun Mi Kim,² Young-Baek Kim,² Gi-Seok Heo,² Jongho Lee,² Eun-Kyung Suh,¹ and Tae Hoon Seo^{*,2}

¹School of semiconductor and Chemical Engineering, Chonbuk National University, Republic of Korea, ²Nano-Photonics Convergence Technology Group, Korea Institute of Industrial Technology, Republic of Korea

MoP-GR-4 (Poster)

11:50 - 13:40

Critical thickness of GaN film in controllable stress-induced self-separation for preparing 2-inch native GaN substratesMengda Li,^{*}1 Yutian Cheng,¹ Tongjun Yu,¹ Jiejun Wu,¹ Jinmi He,² Nanliu Liu,³ Tong Han,¹ and Guoyi Zhang^{1,2,3}¹School of Physics, Peking University, China, ²Sino Nitride Semiconductor CO., LTD., China, ³Dongguan Institute of Optoelectronics, Peking University, China

MoP-GR-5 (Poster)

11:50 - 13:40

Computer simulation of bulk GaN crystal growth from Na-Ga solutionAndrei Vorob'ev,¹ Alexey Kondratyev,¹ Vladimir Kalaev,¹ and Yuji Mukaiyama^{*,2}¹STR Group - Soft Impact, Ltd, Russia, ²STR Japan K.K, Japan

MoP-GR-6 (Poster)

11:50 - 13:40

The optical properties of GaN crystal grown by ammonothermalTengkun Li,^{*,1,2} Guoqiang Ren,^{1,2} Xujun Su,² Jingjing Yao,² Xiaodong Gao,² and Ke Xu^{1,2,3}¹School of Nano Technology and Nano Bionics, University of Science and Technology of China, China, ²Suzhou Institute of Nano-tech and Nano-bionics, Chinese Academy of Sciences, China, ³Suzhou Nanowin Science and Technology Co, Ltd., China

MoP-GR-7 (No Show)

11:50 - 13:40

Study on Transferable GaN Grown on Improved AlN/Graphene Composite SubstrateYanqing Jia,^{*} Jing Ning, Chaochao Yan, Jincheng Zhang, and Yue Hao

Department of Micro Electronic, Xidian University, China

MoP-GR-8 (Poster)

11:50 - 13:40

Reduction of trench defects in InGaN epilayers using Ga-migration-enhanced epitaxyHai-Long WANG,^{*,1} Ze -Sheng Lv,¹ and Hao JIANG^{1,2}¹School of Electronics and Information Technology, Sun Yat-sen University, China, ²State Key Laboratory of Optoelectronic Materials and Technologies, Sun Yat-sen University, China

MoP-GR-9 (Poster)

11:50 - 13:40

High Crystal Quality AlN Film Grown on Hexagonal Nano-circle Concave Patterned Si (111) SubstrateJianfei Shen,^{*} Xuelin Yang, Jie Zhang, Yuxia Feng, and Bo Shen

School of Physics, Peking University, China

MoP-GR-10 (Poster)

11:50 - 13:40

HVPE growth of AlN on stripe patterned sapphire substrates with sputter-deposited annealed AlN filmTaichi Nishimori,^{*,1} Kazuki Yoshimura,¹ Shiyu Xiao,² Kanako Shojiki,¹ and Hideto Miyake^{1,2}¹Grad. School of Eng, Mie University, Japan, ²Grad. School of RIS, Mie University, Japan

MoP-GR-11 (Poster)

11:50 - 13:40

Crystal growth of AlN on Ni-Al solutionArata Kanbara,^{*} Adachi Masayoshi, and Hiroyuki Fukuyama

Institute of Multidisciplinary Research for Advanced Materials, Tohoku University, Japan

MoP-GR-12 (Poster)

11:50 - 13:40

Evaluation of B GaN growth temperature dependence and fabrication of neutron semiconductor detectorsYuri Takahashi,^{*,1} Takayuki Maruyama,¹ Natsuki Yamada,¹ Kazushi Ebara,¹ Yuto Ohta,¹ Hisaya Nakagawa,¹ Shigeyoshi Usami,²Yoshio Honda,³ Hiroshi Amano,^{3,4} Kazunobu Kojima,⁵ Shigefusa Chichibu,^{3,5} Yoku Inoue,¹ Toru Aoki,⁶ and Takayuki Nakano^{1,6}¹Shizuoka University, Japan, ²Nagoya University, Japan, ³IMaSS, Nagoya University, Japan, ⁴Akasaki Research Center, Japan, ⁵IMRAM, Tohoku University, Japan, ⁶R.I.E. Shizuoka University, Japan

MoP-GR-13 (Poster)

11:50 - 13:40

Growth and Characterization of Ultra-Wide Bandgap Gallium Oxide Homoepitaxial Layers Prepared by Plasma-Assisted Molecular-Beam Epitaxy

SOON-KU HONG,* TRONG SI NGO, and DUC DUY LE

Department of Materials Science and Engineering, Chungnam National University, Daejeon 34134, Republic of Korea

MoP-GR-14 (Poster)

11:50 - 13:40

Comparison of thermodynamics on growth of In_2O_3 and Ga_2O_3 by halide vapor phase epitaxy using mono- and tri-halidesNami Tanaka,*¹ Yuya Saimoto,¹ Kenta Nagai,¹ Rie Togashi,² Nao Takekawa,¹ Ken Goto,¹ and Yoshinao Kumagai^{1,3}¹*Department of Applied Chemistry, Tokyo University of Agriculture and Technology, Japan,* ²*Department of Engineering and Applied Sciences, Sophia University, Japan,* ³*Institute of Global Innovation Research, Tokyo University of Agriculture and Technology, Japan*

MoP-GR-15 (Poster)

11:50 - 13:40

Formation and Characterization of Novel Green Phosphor of Semiconductive Nanoporous ZnMnO:P Sejoon Lee,*^{1,2} Youngmin Lee,² and Deuk Young Kim^{1,2}¹*Department of Semiconductor Science, Dongguk University - Seoul, Seoul 04623, Republic of Korea,* ²*Quantum-functional Semiconductor Research Center, Dongguk University - Seoul, Seoul 04623, Republic of Korea*

MoP-GR-16 (Poster)

11:50 - 13:40

Analysis of $-\text{Ga}_2\text{O}_3$ (0001) surface structure using first-principles calculations

Hayato Oyama* and Takahiro Kawamura

Graduate School of Engineering, Mie University, Japan

MoP-GR-17 (Poster)

11:50 - 13:40

Pyramid formation by high pressure and high temperature processing of diamondRei Fukuta,*¹ Yohei Murakami,¹ Ken Otsuyama,¹ Fumitaro Ishikawa,^{1,2} Masafumi Matsushita,^{1,2} Toru Shinmei,² Hiroaki Ohfujii,² and Tetsuo Irifune²¹*Ehime University, Japan,* ²*Ehime University Geodynamics Research center, Japan*

MoP-CH-1 (Poster)

11:50 - 13:40

Investigation on the size effects of micro-Raman scattering in single cone-shape GaN microrod

Hui Liao,* Peijun Wen, Guo Yu, Rui Lang, and Xiaodong Hu

State Key Laboratory for Artificial Microstructure and Mesoscopic Physics, School of Physics, Peking University, China

MoP-CH-2 (Poster)

11:50 - 13:40

Enhanced High Temperature Performance Using by InGaN-ChannelHao Lu,*¹ Xiaohua Ma,¹ Ling Yang,² Bin Hou,¹ Meng Zhang,² Qing Zhu,² Mei Wu,¹ Sheng Wu,¹ Jielong Liu,² and Yue Hao¹¹*School of Microelectronics, Xidian University, China,* ²*School of Advanced Materials and nanotechnology, Xidian University, China*

MoP-CH-3 (No Show)

11:50 - 13:40

Intersubband optical absorption in InGaN/GaN quantum dot with hydrogenic impurity

Yan Xing

School of Physical Science and Technology, Inner Mongolia University, China

MoP-CH-4 (Poster)

11:50 - 13:40

Influence of Dipole Scattering to Level Broadening and Carrier Transport in AlGaIn-based Superlattice Structures

Joosun Yun* and Hideki Hirayama

RIKEN, Japan

MoP-CH-5 (No Show)

11:50 - 13:40

Sub-quantum-well effect on radiative dynamics of Dislocation-free DUV AlGa_N/AlGa_N-based Multiple-Quantum-WellsIdris Ajia,¹ Dhaifallah Almalawi,¹ Zhiqiang Liu,² and Iman S. Roqan^{*1}¹Physical Science and Engineering, King Abdullah University of Science and Technology (KAUST), Thuwal 23955, Saudi Arabia, Saudi Arabia, ²Institute of Semiconductors, Chinese Academy of Science, Beijing 100083, China, China*MoP-CH-6 (No Show)*

11:50 - 13:40

Optical Phonons and Their Transformation in Cylindrical Wurtzite Nitride Core-Multishell Nanowires with Ternary Mixed Crystal EffectJianXia Wang, Yuan Qu,^{*} and Shiliang Ban

Inner Mongolia University, China

MoP-CH-7 (Poster)

11:50 - 13:40

Height of potential barrier formed around V-pits in InGa_N/Ga_N quantum wells on moderate-temperature Ga_N layerSatoshi Kurai,^{*} Kohei Okawa,¹ Ryoga Makio,¹ Junji Gao,¹ Genki Nobata,¹ Naoya Hayashi,¹ Kohei Sugimoto,^{1,2} Narihito Okada,¹ Kazuyuki Tadatomo,¹ and Yoichi Yamada¹¹Yamaguchi University, Japan, ²Ube Industries, Ltd., Japan*MoP-CH-8 (Poster)*

11:50 - 13:40

Optical and electrical characterizations of the V-shaped defects in Fe-doped bulk Ga_NYumin Zhang,^{*,1,2} Jianfeng Wang,^{1,2} Demin Cai,² Yu Xu,^{1,2} Mingyue Wang,^{1,2} Xiaojian Hu,^{1,2} and Ke Xu^{1,2}¹Suzhou Institute of Nano-tech and Nano-Bionics, Chinese Academy of Sciences, China, ²Suzhou Nanowin Science and Technology Co., Ltd., China*MoP-CH-9 (Poster)*

11:50 - 13:40

Relationship between the band gap of In_N/Al_N SLs and lattice distortionYuya Hamaji,^{*,1} Takahiro Kawamura,¹ Toru Akiyama,¹ and Yoshihiro Kangawa²¹Mie Univ., Japan, ²RIAM, Kyushu Univ., Japan*MoP-CH-10 (Poster)*

11:50 - 13:40

Bonding Strength of Polarity-Inverted Ga_N Structure Fabricated by Surface-Activated BondingRyo Tanabe,^{*} Naoki Yokoyama, Masahiro Uemukai, Tomoyuki Tanikawa, and Ryuji Katayama

Osaka University, Japan

MoP-CH-11 (Poster)

11:50 - 13:40

Current mapping of non-polar AlGa_N/Ga_N heterojunction structureJinjuan Du and Shengrui Xu^{*}

School of Microelectronics, Xidian University, China

MoP-CH-12 (Poster)

11:50 - 13:40

Nonradiative Recombination Centers in UVB AlGa_N Quantum Well and Their Temperature Dependence Revealed by Below-Gap Excitation LightM. Ismail Hossain,^{*,1,2} Yuri Itokazu,^{1,3} Shunsuke Kuwaba,^{1,3} Norihiko Kamata,¹ Noritoshi Maeda,³ and Hideki Hirayama³¹Graduate School of Science and Engineering, Saitama University, Saitama 338-8570, Japan, ²Department of Physics, University of Rajshahi, Rajshahi-6205, Bangladesh, ³Quantum Optodevice Lab., RIKEN, Wako, Saitama 351-0198, Japan*MoP-CH-14 (Poster)*

11:50 - 13:40

Resistivity of High-Purity Semi-Insulating 4H-SiC SubstratesChansoon Koo,^{*} Mitsuaki Kaneko, and Tsunenobu Kimoto

Kyoto University, Japan

MoP-CH-15 (Poster)

11:50 - 13:40

Evaluation of heavily B doped HPHT crystals for power device application

Shinichi Shikata,* Kosuke Miyajima, and Naoya Akashi

School of Science and Technology, Kwansei Gakuin University, Japan

MoP-CH-16 (Poster)

11:50 - 13:40

Abnormal Capacitance-Voltage Behavior of 4H-SiC Trench MOS Capacitor with TEOS Oxide

In Ho Kang,* Ogyun Seok, Jeong Hyun Moon, Moon Kyong Na, Hyoung Woo Kim, Sang Cheol Kim, Wook Bahng, and Nam Kyun Kim

Power Semiconductor Research Center, Korea Electrotechnology Research Institute, Republic of Korea

MoP-CH-17 (Poster)

11:50 - 13:40

Influence of strong acid on structural and photoluminescence properties of nano-amorphous graphitic carbon nitride dispersed in nitric acidTakahiro Watanabe,¹ Masaaki Hirai,² Ken-ichi Takarabe,² and Naoki Ohtani*,¹¹*Department of Electronics, Doshisha University, Japan,* ²*Faculty of Science, Okayama University of Science, Japan*

MoP-OD-1 (No Show)

11:50 - 13:40

Effect of p-AlGaN / GaN superlattice on InGaN/GaN multiple quantum wells light-emitting diodes

wenkai yue,* zhimin li, peixian li, xiaowei zhou, and xiaoshun luo

School of Advanced Materials and Nanotechnology, Xidian University, China

MoP-OD-2 (Poster)

11:50 - 13:40

Dual-Wavelength Light-Emitting Diodes with InGaN/GaN Quantum Wells and Mesh-Like Top ElectrodeIrina Khmyrova,*¹ Yohei Nishidate,¹ Yulia Kholopova,² Ivan Maximov,³ and Sergei Shapoval²¹*University of Aizu, Japan,* ²*Russian Academy of Sciences, Russia,* ³*Lund University, Sweden*

MoP-OD-3 (No Show)

11:50 - 13:40

Study of Light Field Distribution in GaN Triangular RidgeCheng Ge,*¹ Menghan Liu,¹ Ru Xu,¹ Jing Zhou,¹ Yunfei Yang,¹ Yimeng Li,¹ Haocheng Peng,¹ Peng Chen,^{1,2} Bin Liu,¹ Zili Xie,¹ Rong Zhang,¹ and Youdou Zheng¹¹*Jiangsu Province Key Laboratory of Advanced Photonic and Electronic Materials and School of Electronic Science and Engineering, Nanjing University, China,* ²*Institute of Optoelectronics of Yangzhou, Nanjing University, China*

MoP-OD-4 (Poster)

11:50 - 13:40

Improved performance of AlGaIn based ultraviolet LEDs using selective-area grown p-GaN contact layerYanan Guo,*^{1,2} Jianchang Yan,^{1,2} Yun Zhang,^{1,2} Junxi Wang,^{1,2} and Jinmin Li^{1,2}¹*Institute of Semiconductors, Chinese Academy of Sciences, China,* ²*University of Chinese Academy of Sciences, China*

MoP-OD-5 (Poster)

11:50 - 13:40

Smoothing AlGaIn surface by photoelectrical chemical etchingZhongming Zheng,*¹ Hao Long,¹ Samuel Matta,² Mathieu Leroux,² Julien Brault,² Lerying Ying,¹ Zhiwei Zheng,¹ and Baoping Zhang¹¹*Department of Electronic Engineering, Xiamen University, China,* ²*Université Côte d'Azur, CNRS, CRHEA, Valbonne, France*

MoP-OD-6 (Poster)

11:50 - 13:40

Enhancement of the electrical and optical properties in GaN-based flip-chip LEDs by optimizing electrode structuresJong-Ho Kim,*¹ Yong Won Lee,² Hyeong-seop Im,¹ and Tae-Yeon Seong^{1,2}¹*Department of Material Science & Engineering, Korea University, Seoul 02841, South Korea, Republic of Korea,* ²*Department of Nanophotonics, Korea University, Seoul 02841, South Korea, Republic of Korea*

MoP-OD-8 (Poster)

11:50 - 13:40

Improvement of light output power of 1024 pixelated flip-chip micro-LED arrays for automotive smart head lamp

Cheol Jeong,* Jea hyeok Lee, Jea Min Lee, Sung Min Cho, Moon Uk Cho, Tae Kyoung Kim, Yu-Jung Cha, Abu Bashar Mohammad Hamidul Islam, and Joon Seop Kwak
sunchon national university, Republic of Korea

MoP-OD-9 (Poster)

11:50 - 13:40

The influence of different sidewall traps for Micro Light Emitting DiodesTe-Jen Kung*,¹ and Yuh-Renn Wu^{1,2}

¹Electronic and Optoelectronic System Research Laboratories, Industrial Technology Research Institute, Taiwan, ²Graduate Institute of Photonics and Optoelectronics and Department of Electrical Engineering, National Taiwan University, Taiwan

MoP-OD-10 (Poster)

11:50 - 13:40

PA-MBE grown III-nitride nanowires on ITO-coated amorphous silica substrate for perovskite solar cell application

Jung-Wook Min,^{*,1} Kwang Jae Lee,² Aditya Prabaswara,¹ Jung-Hong Min,¹ Bekir Türedi,² Yeong Jae Kim,³ Huaafan Zhang,¹ Davide Priante,¹ Jian-Wei Liang,¹ Young Min Song,³ Tien Khee Ng,¹ Osman M. Bakr,² and Boon S. Ooi¹

¹Photonics Laboratory, King Abdullah University of Science and Technology (KAUST), Saudi Arabia, ²Catalysis Center, King Abdullah University of Science and Technology (KAUST), Saudi Arabia, ³School of Electrical Engineering and Computer Science, Gwangju Institute of Science and Technology (GIST), Republic of Korea

MoP-OD-11 (Poster)

11:50 - 13:40

Emission characteristics of AlGaIn / AlGaIn MQWs by improving n-type AlGaIn layer

Kengo Nagata,^{*,1,2} Taiji Yamamoto,^{1,2} Hiroaki Makino,^{1,2} Keita Kataoka,³ Tetsuo Narita,³ and Yoshiki Saito^{1,2}

¹TOYODA GOSEI Co., Ltd., Japan, ²TS Opto Co., Ltd., Japan, ³Toyota Central R&D Labs. Inc., Japan

MoP-OD-12 (No Show)

11:50 - 13:40

Vertical Hybrid Heterojunction for Broadband, Self-powered and Transparent Photodetector

Krishnendu Sarkar,¹ Pooja Devi,^{*,2} and Praveen KUMAR¹

¹Indian Association for the Cultivation of Science, Kolkata, 700032, India, ²Central Scientific Instruments Organization, Sector-30C, Chandigarh-India-160030, India, India

MoP-OD-13 (Poster)

11:50 - 13:40

Fabrication of UVC AlGaIn LEDs on DC-sputtered AlN templates with high-temperature annealing

Yosuke Mogami,^{*,1,2} Atsushi Osawa,³ Kazuto Osaki,³ Yukitake Tanioka,³ Atsushi Maeoka,³ Yuri Itokazu,^{1,2} Shunsuke Kuwaba,^{1,2} Masafumi Jo,¹ Noritoshi Maeda,¹ Hiroyuki Yaguchi,² and Hideki Hirayama¹

¹RIKEN, Japan, ²Department of Science and Engineering, Saitama University, Japan, ³SCREEN Finetech Solutions Co. Ltd., Japan

MoP-OD-14 (Poster)

11:50 - 13:40

Fabrication process development on group III-nitride based three-dimensional light emitting diodes for reduced leakage current

Kie Young Woo,* Young Chul Sim, Kwanjae Lee, Seung-Hyuk Lim, and Yong-Hoon Cho

Department of Physics, Korea Advanced Institute of Science and Technology, Republic of Korea

MoP-OD-15 (Poster)

11:50 - 13:40

Optical-isolation of micro-LED pixels integrated in Si micro-cup substrate

Kohta Sato,^{*,1} Yoshihumi Kamei,¹ Ryosuke Nawa,¹ Shinya Aikawa,² Yasuhisa Usida,³ Takeyoshi Onuma,¹ Tomohiro Yamaguchi,¹ and Tohru Honda¹

¹Department of Applied Physics, School of Advanced Engineering and Department of Electrical Engineering and Electronics, Graduate School of Engineering, Kogakuin University, Japan, ²Department of Electrical and Electronic Engineering, Faculty of Engineering, Kogakuin University, Japan, ³Institute of Materials and Systems for Sustainability (IMass), Nagoya University, Japan

MoP-OD-16 (No Show)

11:50 - 13:40

Full-duplex light communication system with OFDM modulation using InGaN/GaN multiple-quantum-well diodes and waveguideYan Jiang,* Linning Wang, Mingyuan Xie, Zheng Shi, Yuan Jiang, and Yongjin Wang
Peter Grünberg Research Centre, Nanjing University of Posts and Telecommunications, China

MoP-OD-17 (Poster)

11:50 - 13:40

Spatial Non-uniform Avalanche Multiplication in 4H-SiC p-i-n APDsLinlin Su,* Hai Lu, Xiaolong Cai, Dong Zhou, Dunjun Chen, Fangfang Ren, Rong Zhang, and Youdou Zheng
Nanjing University, China

MoP-OD-18 (Poster)

11:50 - 13:40

Low-Leakage-current SiC Schottky barrier photodiode for DUV and EUV detectionZhiyuan Wang,* Dong Zhou, Weizong Xu, Fangfang Ren, Dunjun Chen, Rong Zhang, Youdou Zheng, and Hai Lu
School of Electronic Science and Engineering, Nanjing University, China

MoP-OD-19 (Poster)

11:50 - 13:40

Fabrication of ZnO-based UV photodetector by arc discharge deposition of ZnO nanorodsShahab Sharifi Malvajerdi,*¹ Masoud Abrari,¹ Morteza Ahmadi,¹ Vahid Karimi,¹ Morteza Asemi,¹ Reza Taheri Ghahrizjani,¹ Majid Ghanaatshoar,¹ and Seyed Majid Mohseni²
¹Laser and Plasma Research Institute, Shahid Beheshti University, Iran, ²Faculty of Physics, Shahid Beheshti University, Iran

MoP-OD-20 (Poster)

11:50 - 13:40

Improved thermal characteristics and reliability of blue light-emitting diodes by using via-hole type flip-chip packagingWon Jung Kim,*^{1,2} Chang Man Lim,² Ki Seok Kim,² Jeong Tak Oh,² Hwan-Hee Jeong,² June-O Song,¹ Tae-Yeon Seong,¹ and Hiroshi Amano³
¹Department of Materials Science and Engineering, Korea University, Republic of Korea, ²LED Divisio., LG Innotek Co. Ltd., Paju, Gyeonggi 10842, Republic of Korea, ³Nagoya University, Japan

MoP-ED-1 (Poster)

11:50 - 13:40

High Breakdown Voltage Vertical GaN p-n Junction Diodes with Reversible CharacteristicsHiroshi Ohta,¹ Naomi Asai,¹ Fumimasa Horikiri,² Yoshinobu Narita,² Takehiro Yoshida,² and Tomoyoshi Mishima*¹
¹Hosei University, Japan, ²SCIOCS Co. Ltd., Japan

MoP-ED-2 (Poster)

11:50 - 13:40

Surface activated bonding between GaN and SiC with an ultralow TBRFengwen Mu,*^{1,4} Zhe Cheng,² Seongbin Shin,¹ Samuel Graham,^{2,3} and Tadatomo Suga¹
¹Collaborative Research Center, Meisei University, Japan, ²George W. Woodruff School of Mechanical Engineering, Georgia Institute of Technology, United States of America, ³School of Materials Science and Engineering, Georgia Institute of Technology, United States of America, ⁴Kagami Memorial Research Institute for Materials Science and Technology, Waseda University, Japan

MoP-ED-3 (Poster)

11:50 - 13:40

Dependence of Breakdown Voltage Enhancement on Gate-to-Drain Distance of AlGaIn/GaN HEMTs with High-k Passivation LayerRyo Tomita,* Shingo Ueda, Yuki Kawada, and Kazushige Horio
Faculty of Systems Engineering, Shibaura Institute of Technology, Japan

MoP-ED-4 (No Show)

11:50 - 13:40

Irradiation traps induced by 2060-MeV ⁸⁶Kr²⁶⁺ ions in AlGaIn/GaN HEMTsXiao yan Yan,* Ling Lv, and Zheng zhao Lin
Department of Materials Science and Engineering, Xidian University, China

MoP-ED-5 (Poster)

11:50 - 13:40

Modelling of Trap Mechanism in AlGaIn/GaN Fin-HEMT Current CollapseKailin Ren,^{*} Yung Chii Liang,¹ Chih-Fang Huang,² and Xiao Gong¹¹Department of Electrical & Computer Engineering, National University of Singapore, Singapore, ²Department of Electrical Engineering, National Tsing Hua University, Taiwan

MoP-ED-6 (No Show)

11:50 - 13:40

Normally-Off AlGaIn/GaN MISHEMT Using Charge Storage TechniquePing-Cheng Han,^{*} Zong-Zheng Yan,² Jui-Sheng Wu,² Chia-Hsun Wu,² and Edward Yi Chang^{1,2}¹International College of Semiconductor Technology, National Chiao Tung University, Taiwan, ²Department of Materials Science & Engineering, National Chiao Tung University, Taiwan

MoP-ED-7 (Poster)

11:50 - 13:40

Suppression of Current Collapse in AlGaIn/GaN HEMTs Using a Bilayer SiN PassivationJielong Liu,^{*} Lixiang Chen,¹ Qing Zhu,¹ Fuchun Jia,² Hao Lu,² Siyu Liu,¹ Jiejie Zhu,^{1,2} Ling Yang,^{1,2} Xiaohua Ma,² and Yue Hao²¹School of Advanced Materials and Nanotechnology, Xidian University, China, ²State Key Discipline Laboratory of Wide Bandgap Semiconductor Technology, Xidian University, China

MoP-ED-9 (Poster)

11:50 - 13:40

Precise control in recessed-gate etching for AlGaIn/GaN HEMTs by utilizing photo-electrochemical reactionsYuto Komatsu,^{*} Masachika Toguchi, and Taketomo Sato

Hokkaido University, Japan

MoP-ED-10 (No Show)

11:50 - 13:40

Investigation of Tri-gate and Dual-gate AlGaIn/GaN Fin-HEMTsMeng Zhang,^{*} Ling Yang, Minhan Mi, Bin Hou, Mei Wu, Qing Zhu, Sheng Wu, Yunlong He, and Xiaohua Ma

Xidian University, China

MoP-ED-11 (Poster)

11:50 - 13:40

Termination and Passivation Solutions towards High Avalanche Capability and Ruggedness in Vertical GaN p-i-n Power DiodesKaiwen Nie,^{*} Weizong Xu, Fangfang Ren, Dong Zhou, Dunjun Chen, Rong Zhang, Youdou Zheng, and Hai Lu

School of Electronic Science and Engineering, Nanjing University, Nanjing 210093, China

MoP-ED-12 (Poster)

11:50 - 13:40

Influence of the Surface Charges on the Edge Fringing Capacitance in GaAs and GaN Schottky Barrier DiodesBeatriz Orfao,¹ Beatriz G. Vasallo,¹ Diego Moro-Melgar,² Tomás González,¹ and Javier Mateos^{*}¹¹Universidad de Salamanca, Spain, ²ACST GmbH, Germany

MoP-ED-13 (Poster)

11:50 - 13:40

High-power-figure-of-merit AlGaIn/GaN Schottky Barrier Diode Based on Barrier Recess and Low-temperature AnnealingYu Lu,^{*} Weizong Xu, Fang-Fang Ren, Dong Zhou, Dunjun Chen, Rong Zhang, Youdou Zheng, and Hai Lu

School of Electronic Science and Engineering, Nanjing University, China

MoP-ED-14 (Poster)

11:50 - 13:40

High Breakdown Voltage of AlGaIn/GaN HEMTs with Field Plate for RF ApplicationChun Wang,^{*} Heng-Tung Hsu,^{2,3,4} Ke-Yow Chen,² Ting-Jui Huang,² and Yi Chang^{1,2,3,4}¹Department of Material Science Engineering, National Chiao Tung University, Taiwan, ²International College of Semiconductor Technology, National Chiao Tung University, Taiwan, ³Department of Electrical Engineering, National Chiao Tung University, Taiwan, ⁴Center for Smart Semiconductor Technologies, National Chiao Tung University, Taiwan

MoP-ED-15 (Poster)

11:50 - 13:40

Influence of crystal orientation on the formation of Schottky junctions on gallium oxide

Roman Yatskiv,* Stanislav Tiagulskyi, and Jan Grym

Institute of Photonics and Electronics, CAS, Prague, Czech Republic, Czech Republic

MoP-ED-16 (Poster)

11:50 - 13:40

Detector Mechanism of ZnGa₂O₄ Sensors for NO Gas

SHU-HSIEN LIN,*¹ MIN-RU WU,¹ WEI-ZHONG LI,¹ CHIUNG-YI HUANG,² and RAY-HUA HORNG¹

¹*Institute of Electronics, National Chiao Tung University, Taiwan,* ²*Graduate Institute of Precision Engineering, National Chung Hsing University, Taiwan*

ED1 Vertical Power Devices

Auditorium 13:50-15:05

Chair: Kevin Jing Chen and Yoshio Honda

ED1-1 (Invited)

13:50 - 14:20

Demonstration of vertical GaN planar MOSFET fabricated by all ion implantation process

Shinya Takashima,* Ryo Tanaka, Hideaki Matsuyama, Yuta Fukushima, and Masaharu Edo

Fuji Electric Co., Ltd, Japan

ED1-2 (Invited)

14:20 - 14:50

Outstanding potential of SiC superjunction MOSFET as a next generation 1.2 kV-class power transistor

Shinsuke Harada,* Takeyoshi Masuda, Yusuke Kobayashi, Shinya Kyogoku, Tadao Morimoto, Yusuke Yamashiro, Teruaki Kumazawa, Manabu Takei, and Hajime Okumura

National Institute of Advanced Industrial Science and Technology, Japan

ED1-3 (Oral)

14:50 - 15:05

High-Voltage and Low on-resistance Vertical GaN Schottky Barrier Diode with Reverse p-n Junction Termination

Ru Xu,*¹ Menghan Liu,¹ Jing Zhou,¹ Yunfei Yang,¹ Yimeng Li,¹ Cheng Ge,¹ Haocheng Peng,¹ Peng Chen,^{1,2} Bin Liu,¹ Zili Xie,¹ Rong Zhang,¹ and Youdou Zheng¹

¹*School of Electronic Science and Engineering, Nanjing University, China,* ²*Institute of Optoelectronics of Yangzhou, Nanjing University, China*

GR1 Nanostructures

Meeting Room 13:50-15:05

Chair: Ryuji Katayama and Euijoon Yoon

GRI-1 (Invited)

13:50 - 14:20

Group III-nitride semiconductor nanostructures for room-temperature quantum photonic devices

Yong-Hoon Cho

Korea Advanced Institute of Science and Technology (KAIST), Republic of Korea

GRI-2 (Oral)

14:20 - 14:35

Low-cost fabrication technique of shape-controlled ultra-fine GaN nanostructures by mask-less hydrogen environment anisotropic thermal etching (HEATE) method with ammonia additionYusei Kawasaki,*¹ Yuki Ooe,¹ Yusuke Moriya,¹ Daichi Ito,¹ and Akihiko Kikuchi^{1,2}¹Sophia University, Japan, ²Sophia Photonics Research Center, Japan

GRI-3 (Oral)

14:35 - 14:50

Observation of down-conversion behavior in ZnO:TM,Yb/ZnO core-shell nanowires

Jun Tatebayashi,* Tokuhito Nakajima, Masao Mishina, Dolf Timmerman, Shuhei Ichikawa, and Yasufumi Fujiwara

Osaka University, Japan

GRI-4 (Oral)

14:50 - 15:05

Red Emitting InGaN-based Ordered Nanocolumns Exhibiting Photonic Crystal Effects at 671 nmKeiji Takimoto,*¹ Kazuki Narita,¹ Keigo Yoshida,³ Takao Oto,⁴ Tomohiro Yamaguchi,³ Tohru Honda,³ Takeyoshi Onuma,³ Rie Togashi,¹ Ichiro Nomura,^{1,2} and Katsumi Kishino^{1,2}¹Sophia University, Japan, ²Sophia Nanotechnology Center, Japan, ³Kogakuin University, Japan, ⁴Yamagata University, Japan

Break

15:05 - 15:35

OD1 Photonic Devices

Auditorium 15:35-17:05

Chair: Akihiko Kikuchi and Rong Zhang

OD1-1 (Invited)

15:35 - 16:05

Recent Progress in High-Brightness Photonic-Crystal Lasers

Susumu Noda* and Menaka De Zoysa

Kyoto University, Japan

OD1-2 (Oral)

16:05 - 16:20

Continuous-Wave Electrically Injected GaN-on-Si Microdisk Laser DiodesJin Wang,*^{1,2} Meixin Feng,² Jianxun Liu,² Yingnan Huang,² Xiujian Sun,² Qian Sun,² Xinhe Zheng,¹ and Hui Yang²¹University of Science and Technology Beijing, China, ²Key Laboratory of Nano-devices and Applications, Suzhou Institute of Nano-Tech and Nano-Bionics, Chinese Academy of Sciences, China

OD1-3 (Oral)

16:20 - 16:35

Design and Fabrication of GaN Doubly-Resonant Waveguide Microcavity SHG DeviceTakumi Nagata,*¹ Masahiro Uemukai,¹ Toshiki Hikosaka,² Shinya Nunoue,² Takaya Morikawa,¹ Yasufumi Fujiwara,¹ Tomoyuki Tanikawa,¹ and Ryuji Katayama¹¹Osaka University, Japan, ²Toshiba Corporation, Japan

OD1-4 (Oral)

16:35 - 16:50

Effects of lateral optical confinement in GaN VCSELs with double dielectric DBRsRongbin Xu,*¹ Yang Mei,¹ Huan Xu,¹ Leiyong Ying,¹ Zhiwei Zheng,¹ Hao Long,¹ Jianping Liu,² and Baoping Zhang¹¹Department of Electronic Engineering, Xiamen University, China, ²Suzhou Institute of Nano-tech and Nano-bionics, Chinese Academy of Sciences, China

OD1-5 (Oral)

16:50 - 17:05

GaN quantum dots on deep-UV distributed Bragg reflector

Frank Bertram,^{*1} Hannes Schürmann,¹ Gordon Schmidt,¹ Christoph Berger,¹ Sebastian Metzner,¹ Peter Veit,¹ Armin Dadgar,¹ Andre Strittmatter,¹ Jürgen Christen,¹ Stefan Kalinowski,² Stefan Jagsch,² and Axel Hoffmann²

¹Institute of Physics, Otto-von-Guericke-University Magdeburg, Germany, ²Institute of Solid-State Physics, Technical University Berlin, Germany

GR2 Novel Growth Technology

Meeting Room 15:35-17:05

Chair: Hajime Fujikura and Jianfeng Wang

GR2-1 (Invited)

15:35 - 16:05

Homoepitaxial growth of β -Ga₂O₃ by halide vapor phase epitaxy for the preparation of epitaxial wafers for vertical power device application

Yoshinao Kumagai,^{*1,2} Ken Goto,¹ Keita Konishi,³ Hisashi Murakami,^{1,2} Akito Kuramata,³ Shigenobu Yamakoshi,⁴ Bo Monemar,⁵ and Masataka Higashiwaki⁶

¹Department of Applied Chemistry, Tokyo University of Agriculture and Technology, Japan, ²Institute of Global Innovation Research, Tokyo University of Agriculture and Technology, Japan, ³Novel Crystal Technology, Inc., Japan, ⁴Tamura Corporation, Japan, ⁵Department of Physics, Chemistry and Biology, Linköping University, Sweden, ⁶National Institute of Information and Communications Technology, Japan

GR2-2 (Invited)

16:05 - 16:35

Development of 4H-SiC single crystal substrates for power device applications

Noboru Ohtani

Kwansei Gakuin University, School of Science and Technology, Japan

GR2-3 (Oral)

16:35 - 16:50

Comparative Study of Low-Temperature Grown Hexagonal Boron Nitride on Sapphire by Continuous Flow Mode and Pulsed Flow Mode Epitaxy

Muzafar Ahmad Rather,^{*1} Loganathan Ravi,¹ Kun-Lin Lin,² Chien-Ting Wu,² Tung-Yuan Yu,² and Jen-Inn Chyi¹

¹National Central University, Taiwan, ²National Applied Research Laboratories, Taiwan Semiconductor Research Institute, Taiwan

GR2-4 (Oral)

16:50 - 17:05

High-temperature annealing induced evolution of strain in AlN epitaxial films grown on sapphire substrates

Mingxing Wang,^{*} Fujun Xu, Zhixin Qin, Jiaming Wang, Yuanhao Sun, Nan Xie, Na Zhang, Jing Lang, and Bo Shen

State Key Laboratory of Artificial Microstructure and Mesoscopic Physics, School of Physics, Peking University, China

November 12 (Tuesday)

Plenary 2

Auditorium 09:00-10:40

Chair: Hiroyuki Fukuyama and Yoichi Kawakami

PL-3 (Plenary)

09:00 - 09:50

Wide-bandgap semiconductors as key materials in realizing zero emission of greenhouse gases

Hiroshi AMANO

Nagoya University, Japan

PL-4 (Plenary)

09:50 - 10:40

Self-passivated high-efficiency micro-LEDs using sapphire nano-membrane technology

Euijoon Yoon,^{*1,2,3} Jongmyeong Kim,¹ Seungmin Lee,¹ Jehong Oh,¹ Jungel Ryu,¹ and Yongjo Park¹

¹Department of Materials Science and Engineering, Seoul National University, Republic of Korea, ²Research Institute of Advanced Materials, Seoul National University, Republic of Korea, ³Inter-university Semiconductor Research Center, Seoul National University, Republic of Korea

Break

10:40 - 11:10

ED2 HEMT

Auditorium 11:10-12:40

Chair: Kei-May Lau and Shinya Takashima

ED2-1 (Invited)

11:10 - 11:40

Integration on GaN-on-Si p-GaN gate HEMT Platform

Kevin Jing Chen* and Jin Wei

The Hong Kong University of Science and Technology, Hong Kong

ED2-2 (Oral)

11:40 - 11:55

Improved Device Performance by Integrating Schottky p-GaN Gate Diode and E-mode p-GaN Gate HEMT for 650 V Application

Yi-nan Zhong,¹ Wei-Cheng Ho,¹ Yu-Chen Lai,¹ Yue-ming Hsin,^{*1} Yuan-Ta Hsieh,² Hann-Huei Tsai,² and Ying-Zong Juang²

¹Department of Electrical Engineering, National Central University, Taiwan, ²Taiwan Semiconductor Research Institute, National Applied Research Laboratories, Taiwan

ED2-3 (Oral)

11:55 - 12:10

A Method Based on Transitional-Recessed-Gate Technology to Improve HEMTs' Gain and Linearity Characteristics

Wu Sheng,^{*} Mi Minhan, Ma Xiaohua, Yang Ling, Zhang Meng, Wu Mei, Lu Yang, Zhang Hengshuang, Yi Chupeng, and Hao Yue
Xidian University, Xi'an 710071, China, China

ED2-4 (Oral)

12:10 - 12:25

Impact of selective thermal etching in NH₃/H₂ mixed atmosphere on crystal quality of Al-GaN/GaN heterostructuresYuki Yoshiya,* Takuya Hoshi, Hiroki Sugiyama, and Hideaki Matsuzaki
NTT Device Technology Labs, NTT Corporation, Japan

ED2-5 (Oral)

12:25 - 12:40

Evaluation of Interfacial Charges at GaN/AlGaN Interfaces Grown by MOVPE using Triethyl-galliumTakuya Hoshii,*¹ Hiromasa Okita,¹ Taihei Matsushashi,¹ Indraneel Sanyal,² Yu-Chih Chen,² Ying-Hao Ju,² Akira Nakajima,³ Kuniyuki Kakushima,¹ Hitoshi Wakabayashi,¹ Jen-Inn Chyi,² and Kazuo Tsutsui¹
¹Tokyo Tech, Japan, ²National Central Univ., Taiwan, ³AIST, Japan**GR3 Vapor Phase Epitaxy**

Meeting Room 11:10-12:40

Chair: Michal Stanislaw Bockowski and Hisashi Murakami

GR3-1 (Invited)

11:10 - 11:40

HVPE for GaN and AlN epi-layer growthHajime Fujikura,* Taichiro Konno, Takeshi Kimura, Fumimasa Horikiri, and Takehiro Yoshida
SCIOCS, Japan

GR3-2 (Invited)

11:40 - 12:10

Bulk GaN substrate growth by HVPE technology for GaN-on-GaN devicesJianfeng Wang,*^{1,2} Ke Xu,^{1,2} Guoqiang Ren,^{1,2} Yu Xu,^{1,2} Demin Cai,² Yumin Zhang,^{1,2} Mingyue Wang,^{1,2} Zongyao Li,² and Xiaojian Hu^{1,2}
¹Suzhou Institute of Nano-tech and Nano-bionics, Chinese Academy of Sciences, China, ²Suzhou Nanowin Science and Technology Co. Ltd., China

GR3-3 (Oral)

12:10 - 12:25

Impact of the Growth Temperature on GaN Crystal Characteristics by Trihalide Vapor Phase EpitaxyErina Miyata,*¹ Syoma Ohtaki,¹ Kenji Iso,^{1,2} Hisashi Murakami,¹ and Akinori Koukitu¹¹Department of engineering, Tokyo University of Agriculture and Technology, Japan, ²Mitsubishi Chemical Corporation, Japan

GR3-4 (Oral)

12:25 - 12:40

Study on halide vapor phase epitaxy growth of twin-free cubic-indium oxide and its carrier propertiesKen Goto,*¹ Kenta Nagai,¹ Yuya Saimoto,¹ Nami Tanaka,¹ Nao Takekawa,¹ Rie Togashi,² and Yoshinao Kumagai^{1,3}¹Department of Applied Chemistry, Tokyo University of Agriculture and Technology, Japan, ²Department of Engineering and Applied Science, Sophia University, Japan, ³Institute of Global Innovation Research, Tokyo University of Agriculture and Technology, Japan

Poster Session B

Tunnel Gallery 12:40-14:30

TuP-GR-1 (Poster)

12:40 - 14:30

AlN growth behaviors in ammonia-free high temperature MOVPE

XUQIANG SHEN,* K. Kojima, and H. Okumura

National Institute of Advanced Industrial Science and Technology (AIST), Japan

TuP-GR-2 (Poster)

12:40 - 14:30

Characterization of AlN Microspheres Grown by HVPE methodGang Seok Lee,*¹ Kyoung Hwa Kim,¹ Hyung Soo Ahn,¹ Min Yang,¹ Sam Nyung Yi,¹ Injun Jeon,² Chae Ryong Cho,² Jae Hak Lee,³ and Suck-Whan Kim⁴¹Department of Electronic Materials Engineering, Korea Maritime and Ocean University, Republic of Korea, ²Department of Nanoenergy Engineering and Department of Nano Fusion Technology, Pusan National University, Republic of Korea, ³KDMC Co., Ltd, Republic of Korea, ⁴Department of Physics, Andong National University, Republic of Korea

TuP-GR-3 (Poster)

12:40 - 14:30

Growth of Al_{0.55}Ga_{0.45}N thick films on AlN templates with nano-sized patterned groovesShohei Teramura,*¹ Yusuke Sakuragi,¹ Shinji Yasue,¹ Shunya Tanaka,¹ Yuya Ogino,¹ Motoaki Iwaya,¹ Tetsuya Takeuti,¹ Satoshi Kamiyama,¹ Sho Iwayama,^{1,3} Isamu Akasaki,^{1,2} and Hideto Miyake³¹Department of Materials Science and Engineering Meijo University, Japan, ²Akasaki Research Center, Nagoya University, Japan, ³Graduate School of Regional Innovation Studies, Mie University, Japan

TuP-GR-5 (Poster)

12:40 - 14:30

Effect of the miscut angle of GaN substrate on InGaN/GaN MQW grown by metalorganic vapor phase epitaxyZhibin Liu,*^{1,3,4} Shugo Nitta,² Yoshio Honda,² Markus Pristovsek,² and Hiroshi Amano²¹Department of Electrical Engineering and Computer Science, Nagoya University, Japan, ²Institute of Materials and Systems for Sustainability, Nagoya University, Japan, ³Institute of Semiconductors, Chinese Academy of Science, China, ⁴University of Chinese Academy of Sciences, China

TuP-GR-6 (Poster)

12:40 - 14:30

Mechanism of AlN Fabrication by Substitutional Reaction between Al Layer and GaN Substrate

Marsetio Noorprajuda,* Makoto Ohtsuka, Masayoshi Adachi, and Hiroyuki Fukuyama

Institute of Multidisciplinary Research for Advanced Materials (IMRAM), Tohoku University, Japan

TuP-GR-7 (Poster)

12:40 - 14:30

High crystallinity GaN film growth by sputtering with low oxygen concentration GaN targetYuya Tsuchida,*¹ Yuya Suemoto,¹ Masami Mesuda,¹ Hideto Kuramochi,¹ Liwen Sang,² and Takahiro Nagata²¹Tosoh corporation, Japan, ²National Institute for Materials Science, Japan

TuP-GR-8 (Poster)

12:40 - 14:30

Effects of Adatom Kinetics on Facet Formation of GaN during Metalorganic Vapor Phase Epitaxy

Yuki Seta,* Abdul Muizz Pradipto, Toru Akiyama, Kohji Nakamura, and Tomonori Ito

Department of Physics Engineering, Mie University, Japan

TuP-GR-9 (Poster)

12:40 - 14:30

Thick AlN epilayer grown by using mixed-source hydride vapor phase epitaxy methodKyoung Hwa Kim,*¹ Sang Woo Kim,¹ Gang Seok Lee,¹ Hyung Soo Ahn,¹ Min Yang,¹ Sam Nyung Yi,¹ Injun Jeon,² Chae Ryong Cho,² and Suck-Whan Kim³¹Department of Electronic Materials Engineering, Korea Maritime and Ocean University, Republic of Korea, ²Department of Nanoenergy Engineering and Department of Nano Fusion Technology, Republic of Korea, ³Department of Physics, Andong National University, Republic of Korea

TuP-GR-10 (Poster)

12:40 - 14:30

Theoretical study for the adsorption-desorption behavior of stepped III-nitrides during MOVPE growth

Takumi Ohka,* Toru Akiyama, Abdul Muizz Pradipto, Kohji Nakamura, and Tomonori Ito

Department of Physics Engineering, Mie University, Japan

TuP-GR-11 (No Show)

12:40 - 14:30

AlN Epitaxial Growth with Very High Growth Rate by HT MOCVD

Byoungtak Lee, Sain Hong, Hwanuk Shin, Taesanbukdoo Lim, and Minho Choi*

TOP Engineering, Republic of Korea

TuP-GR-13 (Poster)

12:40 - 14:30

Formation of 3C-SiC thin film by Si surface carbonization for growth of GaN on Si substrates

Jianwei Wang,* Yifu Zhu, Takeshi Momose, Yukihiko Shimogaki, and Momoko Deura

Department of Material Engineering, University of Tokyo, Japan

TuP-GR-14 (Poster)

12:40 - 14:30

Numerical study on impact of solidification kinetic for β -Ga₂O₃ crystal growth by Czochralski methodYuji Mukaiyama,*¹ Masaya Iizuka,¹ Andrei Vorob'ev,² Vladimir Artemyev,² Vasif Mamedov,² and Vladimir Kalaev²¹STR Japan K.K, Japan, ²STR Group - Soft Impact, Ltd, Russia

TuP-GR-15 (Poster)

12:40 - 14:30

Removal Process of Residual Si Impurities on Ga₂O₃ Substrate by CF₄ Reactive Ion Etching Treatment

Yoshiaki Nakata and Masataka Higashiwaki*

National Institute of Information and Communications Technology, Japan

TuP-GR-16 (No Show)

12:40 - 14:30

Solid-liquid interface control and optimization of Ga₂O₃ crystal growth by EFG method

Zhitai Jia,* Wenxiang Mu, Bo Fu, Jin Zhang, and Xutang Tao

State key lab of crystal materials, Shandong Univeristy, China

TuP-GR-17 (Poster)

12:40 - 14:30

Crystal structure of MgZnO deposited by RF sputteringMaki Kushimoto,*¹ Tadayoshi Sakai,¹ Manato Deki,² Yoshio Honda,^{2,3} and Hiroshi Amano^{2,4}¹Dept. of Electronics, Nagoya Univ., Japan, ²IMaSS, Japan, ³Institute of Advanced Resarch, Japan, ⁴Akasaki RC, Japan

TuP-CH-1 (No Show)

12:40 - 14:30

Optical characterization of light extraction behaviors on the light emitting diodes grown on the different patterning substrates

SangMook KIM* and Jong Hyeob Baek

Korea Photonics Technology Institute, Republic of Korea

TuP-CH-2 (No Show)

12:40 - 14:30

Modulation of nanochannel geometry on self-heating in Tri-gate Nanowire GaN HEMTs on Silicon SubstrateMei Wu,* Qing Zhu, Meng Zhang, Xinchuang Zhang, Ling Yang, Xiaohua Ma, and Yue Hao
State Key Discipline Laboratory of Wide Band-Gap Semiconductor Technology, Xidian University, China

TuP-CH-3 (No Show)

12:40 - 14:30

Carrier Dynamics of Removing Excitation Pulse in InGaN Quantum DotsMing Tian,*^{1,2} Honghui Liu,¹ Jianping Liu,³ Hui Yang,³ and Zhe Chuan Feng^{1,2}
¹Laboratory of optoelectronic materials & detection technology, Guangxi Key Laboratory for the Relativistic Astrophysics, School of Physics Science & Technology, Guangxi University, China, ²Center on Nanoenergy Research, Guangxi University, China, ³Suzhou Institute of Nano-tech and Nano-bionics, Chinese Academy of Sciences, China

TuP-CH-4 (Poster)

12:40 - 14:30

Optical Properties of GaN-Based Triangular Ridge Structures under High ExcitationJing Zhou,* Menghan Liu, Ru Xu, Yunfei Yang, Cheng Ge, Haocheng Peng, Peng Chen, Bin Liu, Zili Xie, Rong Zhang, and Youdou Zheng
School of Electronic Science and Engineering, Nanjing University, China

TuP-CH-5 (No Show)

12:40 - 14:30

Carrier dynamics in enhanced MQW light emitting diode structures via V-pitsIdris Ajja,¹ Zhiqiang Liu,² Paul Edwards,³ Robert W. Martin,³ and Iman S. Roqan*¹
¹Physical Science and Engineering, King Abdullah University of Science and Technology (KAUST), Thuwal 23955, Saudi Arabia, Saudi Arabia, ²Institute of Semiconductors, Chinese Academy of Science, Beijing 100083, China, China, ³Department of Physics, SUPA, University of Strathclyde, Glasgow, G4 0NG, United Kingdom, United Kingdom

TuP-CH-6 (Poster)

12:40 - 14:30

Evaluation of dislocations in AlN single crystal substratesYongzhao YAO,*¹ Yukari ISHIKAWA,¹ Yoshihiro SUGAWARA,¹ Narihito OKADA,² and Kazuyuki TADATOMO²
¹Japan Fine Ceramics Center, Japan, ²Yamaguchi Univ., Japan

TuP-CH-7 (Poster)

12:40 - 14:30

Leakage Current Mechanisms of Fully Recessed GaN SBDs with Low Turn-ON VoltageYanni Zhang,* Jincheng Zhang, Hong Zhou, Tao Zhang, and Yue Hao
State Key Discipline Laboratory of Wide Band Gap Semiconductor Technology, School of Microelectronics, Xidian University, China

TuP-CH-8 (Poster)

12:40 - 14:30

Study of single-crystalline GaN converted from β -Ga₂O₃ filmYuewen Li,* Xiangqian Xiu, Xuemei Hua, Zili Xie, Peng Chen, Bin Liu, Dunjun Chen, Rong Zhang, and Youdou Zheng
School of Electronic Science and Engineering, Nanjing University, China

TuP-CH-9 (Poster)

12:40 - 14:30

Surface Plasmon Coupling around Lateral Interface toward InGaN Nanocolumn Based Plasmonic LEDs with High EfficienciesMichitaka Oigawa,*¹ Koichi Okamoto,² Rie Togashi,³ Katsumi Kishino,⁴ and Takao Oto¹
¹Yamagata University, Japan, ²Osaka Prefecture University, Japan, ³Sophia University, Japan, ⁴Sophia Nanotechnology Research Center, Japan

TuP-CH-10 (Poster)

12:40 - 14:30

Development of AlGaIn Photodiode for UV-C detectionThu Thi Thuy Pham,* Hyungtak Kim, Ho-Kyoung Lee, Hyunsik Shin, and Ho-Young Cha
Department of Electronic and Electrical Engineering, Hongik University, Republic of Korea

TuP-CH-11 (Poster)

12:40 - 14:30

Electronic structures of InGaN alloysMasataka Imura*,¹ and Yuichi Ota²¹National Institute for Material Science, Japan, ²Tokyo Metropolitan Industrial Technology Research Institute, Japan

TuP-CH-12 (Poster)

12:40 - 14:30

Influence of Carbon Doping on the Background n-type Impurity in GaNZhen xing Liu*,¹ Liu an Li,¹ Ya wen Zhao,¹ Tao tao Que,¹ Jin wei Zhang,¹ Xin Gu,¹ Qiu ling Qiu,¹ Qian shu Wu,¹ and Yang Liu^{1,2}¹School of Electronics and Information Technology, Sun Yat-Sen University, China, ²State Key Laboratory of Optoelectronic Materials and Technologies, Sun Yat-sen University, China

TuP-CH-13 (Poster)

12:40 - 14:30

Surface passivation effect by various oxidation treatment on InGaN/GaN nanostructures fabricated by HEATEDaichi Ito*,¹ Yuki Ooe,¹ Yusei Kawasaki,¹ Yuta Moriya,¹ and Akihiko Kikuchi^{1,2}¹Sophia University, Japan, ²Sophia Photonics Research Center, Japan

TuP-CH-14 (Poster)

12:40 - 14:30

Control of the composition range for bipolar doping in Ni_xCd_{1-x}O alloys by oxygen stoichiometry and Li dopingKingsley Onyekachi Egbo*,¹ Chao Ping Liu,^{1,2} and Kin Man Yu^{1,3}¹Department of Physics, City University of Hong Kong, Hong Kong, ²Department of Physics, College of Science, Shantou University, China,³Department of Materials Science and Engineering, City University of Hong Kong, Hong Kong

TuP-CH-15 (Poster)

12:40 - 14:30

VUV Exciton Emission Spectra of MgO Single CrystalsKanta Kudo*,¹ Shoma Hoshi,² Mizuki Ono,¹ Yuki Fujiwara,¹ Kentaro Kaneko,^{2,3,4} Tomohiro Yamaguchi,¹ Tohru Honda,¹ Shizuo Fujita,^{2,4} and Takeyoshi Onuma¹¹Department of Applied Physics, School of Advanced Engineering, Graduate School of Engineering, Kogakuin University, Japan,²Department of Electronic Science and Engineering, Kyoto University, Japan, ³Engineering Education Research Center, Kyoto University, Japan, ⁴Engineering Education Research Center, Kyoto University, Japan

TuP-CH-16 (Poster)

12:40 - 14:30

Theoretical Study of Band Structure Effects on Impact Ionization Coefficients in Wide-bandgap SemiconductorsHajime Tanaka*,^{1,2} Nobuya Mori,² and Tsunenobu Kimoto¹¹Kyoto University, Japan, ²Osaka University, Japan

TuP-OD-1 (Poster)

12:40 - 14:30

Flexible metal mesh/ultrathin ITO hybrid transparent electrode and their application for GaN-based light-emitting diodes

Woo-Lim Jeong*, Jung-Hong Min, Hoe-Min Kwak, and Dong-Seon Lee

Gwangju Institute of Science and Technology, Republic of Korea

TuP-OD-2 (Poster)

12:40 - 14:30

High-gain visible-blind AlGaIn/GaN heterojunction phototransistor with a polarization-doped p-type baseLijie Sun,¹ Zesheng Lv,¹ and Hao JIANG*,^{1,2}¹School of Electronics and Information Technology, Sun Yat-sen University, China, ²State Key Laboratory of Optoelectronic Materials and Technologies, Sun Yat-sen University, China

TuP-OD-3 (Poster)

12:40 - 14:30

Simulation of light extraction efficiency in multi-quantum-shell-LED fabricated on patterned sapphire substrate (PSS)Mizuki Terazawa,^{*} Masaki Ohya,^{1,3} Kazuyoshi Iida,^{1,3} Naoki Sone,^{1,4} Nanami Goto,¹ Hideki Murakami,¹ Yu Okamoto,¹ Weifang Lu,¹ Satoshi Kamiyama,¹ Tetsuya Takeuchi,¹ Motoaki Iwaya,¹ and Isamu Akasaki^{1,2}¹Meijo University, Japan, ²Akasaki Research Center, Nagoya University, Japan, ³Toyoda Gosei Co., Ltd, Japan, ⁴Koito Manufacturing CO., LTD, Japan

TuP-OD-4 (Poster)

12:40 - 14:30

Ni/NiO_x nanocatalyst coated n-GaN for efficient photoelectrochemical water splittingYen-Hsien Yeh,^{*} Chi-Huang Chuang, Tzu-Yi Yu, and Yuh-Jen Cheng

Research Center for Applied Sciences, Academia Sinica, Taiwan

TuP-OD-5 (Poster)

12:40 - 14:30

Ultraviolet C Light-Emitting Diode with Active Mesa Stripes and Inclined Sidewalls for Enhanced TM mode Light EmissionWei En Chang,^{1,2} Chia Lung Tsai,^{*} Yuh Renn Wu,¹ Hsueh Hsing Liu,¹ Yi Keng Fu,¹ and Chia Feng Lin²¹Electronic and Optoelectronic System Research Laboratories, Industrial Technology Research Institute, Taiwan, ²Department of Materials Science and Engineering, National Chung Hsing University, Taiwan

TuP-OD-8 (Poster)

12:40 - 14:30

Fabrication of nonpolar InGaN/GaN single-quantum-well-based nanopillar green light-emitting diode using self-assembled nanodotsAbu Bashar Mohammad Hamidul Islam,^{*} Min Joo Park, Yu-Jung Cha, and Joon Seop Kwak

sunchon national university, Republic of Korea

TuP-OD-9 (Poster)

12:40 - 14:30

Mg ion-implantation based GaN p-i-n photodiode for visible-blind ultraviolet detectionWeizong Xu,^{*} Yating Shi, Fangfang Ren, Dong Zhou, Linlin Su, Qing Liu, Jiandong Ye, Dunjun Chen, Rong Zhang, Youdou Zheng, and Hai Lu

School of Electronic Science and Engineering, Nanjing University, China

TuP-OD-10 (Poster)

12:40 - 14:30

Improved performance of GaN-based green laser diodes by using ITO cladding layers

Jianping Liu

Suzhou Institute of Nano-tech and Nano-bionics, Chinese Academy of Science, China

TuP-OD-11 (Poster)

12:40 - 14:30

Effects of the AlGaIn/GaN superlattice electron blocking layer on efficiency characteristics of green light emitting diodesRuoshi Peng, Shengrui Xu,^{*} and Hongchang Tao

Wide Bandgap Semiconductor Technology Disciplines State Key Laboratory, Xidian University, China

TuP-OD-12 (Poster)

12:40 - 14:30

Design of Deep Ultraviolet Second Harmonic Generation Device with Double-Layer Polarity-Inverted AlN WaveguideAsahi Yamauchi,^{*} Tenta Komatsu,¹ Kazuhisa Ikeda,¹ Kenjiro Uesugi,² Kanako Syojiki,² Hideto Miyake,² Toshiki Hikosaka,³ Sinya Nunoue,³ Takaya Morikawa,¹ Yasufumi Fujiwara,¹ Masahiro Uemukai,¹ Tomoyuki Tanikawa,¹ and Ryuji Katayama¹¹Osaka Univ., Japan, ²Mie Univ., Japan, ³Toshiba Corp., Japan

TuP-OD-13 (Poster)

12:40 - 14:30

Improved emission performance of N-polar GaN-based blue-violet light-emitting diodes with a polarization-induced tunneling junction

Yuanta Zhang,* Gaoqiang Deng, Ye Yu, Yang Wang, and Baolin Zhang

State Key Laboratory of Integrated Optoelectronics, College of Electronic Science and Engineering, Jilin University, China

TuP-OD-14 (Poster)

12:40 - 14:30

Optical control of room temperature exciton polariton condensate in one-dimensional structure

Hyun Gyu Song,* Sunghan Choi, Min Sik Kwon, Kie Young Woo, Chung Hyun Park, and Yong-Hoon Cho

Korea Advanced Institute of Science and Technology (KAIST), Republic of Korea

TuP-OD-15 (No Show)

12:40 - 14:30

Dual-functional InGaN/GaN MQW Diode for Auto Brightness Control

Xumin Gao,* Xinyu Xu, Kang Fu, Linning Wang, Yuan Jiang, and Yongjin Wang

College of Telecommunications and Information Engineering, Nanjing University of Posts and Telecommunications, China

TuP-OD-16 (Poster)

12:40 - 14:30

Modulation of Circadian Rhythm and Growth Rate of Neurospora Crassa by Using Green Light LEDPEIJUN WEN,*^{1,2} FUYUN TAN,^{1,2} HUI LIAO,^{1,2} and XIAODONG HU^{1,2}¹*School of Physics, Peking University, China,* ²*Research Center For Wide Gap Semiconductor of Peking University, China*

TuP-OD-17 (Poster)

12:40 - 14:30

Room-temperature Weak X-ray Detection Based on 25 mm² 4H-SiC p-i-n Diodes

Qing Liu,* Weizong Xu, Heng Zhang, Hao Dong, Dong Zhou, Fangfang Ren, Dunjun Chen, Rong Zhang, Youdou Zheng, and Hai Lu

School of Electronic Science and Engineering, Nanjing University, China

TuP-OD-18 (Poster)

12:40 - 14:30

Ion implantation effect on DUV photodetectors performance of Ga₂O₃ epilayer grown by MOCVD

PENG HSUAN HUANG,* YUAN CHU SHEN, LIANG HSING LAI, and RAY HUA HONG

Institute of Electronics Engineering, National Chiao Tung University, Taiwan

TuP-OD-19 (Poster)

12:40 - 14:30

Realization of a Self-powered InGaZnO MSM UV photodetector by UV-induced asymmetric Schottky Barrier

Yu-Ru Liu and Chun-Ying Huang*

Department of Applied Materials and Optoelectronics Engineering, National Chi Nan University, Taiwan

TuP-OD-20 (Poster)

12:40 - 14:30

Intramolecular energy transfer effect of Erbium complexes doped optical waveguide amplifier pumped by LEDDan Zhang,*¹ Hong Zhan,¹ Zhensheng Lin,¹ Wang Fan,¹ Zhongming Zheng,¹ Hao Long,¹ Zhiwei Zheng,¹ Leiying Ying,¹ Baoping Zhang,¹ and Guomei He²¹*School of Electronic Science and Engineering(National Model Microelectronics College), Xiamen University, China,* ²*Department of Materials Science and Engineering, College of Materials, Xiamen University, China*

TuP-ED-1 (Poster)

12:40 - 14:30

Simple Photoelectrochemical Etching for GaN HEMT ApplicationFumimasa Horikiri,*¹ Noboru Fukuhara,¹ Yoshinobu Narita,¹ Takehiro Yoshida,¹ Masachika Toguchi,² Kazuki Miwa,² and Take-tomo Sato²¹*SCIOCS Co. Ltd, Japan,* ²*Hokkaido Univ., Japan*

TuP-ED-2 (No Show)

12:40 - 14:30

Enhancement of channel conductivity and suppression of current collapse in C-doped GaN buffer by using the Si δ -doped AlGaIn back barrierLing Yang,^{*}1 Meng Zhang,¹ Bin Hou,² Minhan Mi,² Mei Wu,² Qing Zhu,¹ Jiejie Zhu,² Xiaohua Ma,² and Yue Hao²¹School of advanced materials and nanotechnology, Xidian University, China, ²School of Microelectronics, Xidian University, China*TuP-ED-3 (Poster)*

12:40 - 14:30

Effects of Surface Oxide Reduction Prior to Metallization on Electrical Properties of GaN-on-GaN Schottky Diodes

Kazuki Isobe* and Masamichi Akazawa

Hokkaido University, Japan

TuP-ED-4 (No Show)

12:40 - 14:30

Fin-Gated Nanochannel Array GaN-based Metal-Oxide-Semiconductor High-Electron Mobility TransistorsChing-Ting Lee^{*,1,2} and Hsin-Ying Lee²¹Department of Electrical Engineering, Yuan Ze University, Taoyuan 320, Taiwan, Republic of China, Taiwan, ²Department of Photonics, National Cheng Kung University, Tainan 701, Taiwan, Republic of China, Taiwan*TuP-ED-5 (Poster)*

12:40 - 14:30

Evaluation of Radical Production Rate from S₂O₈²⁻ ions for GaN EtchingMasachika Toguchi,^{*}1 Kazuki Miwa,¹ Fumimasa Horikiri,² Noboru Fukuhara,² Yoshinobu Narita,² Takehiro Yoshida,² and Take-tomo Sato¹¹Hokkaido University, Japan, ²SCIOCS Co. Ltd., Japan*TuP-ED-6 (Poster)*

12:40 - 14:30

A GaN Power Amplifier MMIC for Ka band Satellite CommunicationChupeng Yi,^{*}1 Yang Lu,² Hengshuang Zhang,² Ziyue Zhao,¹ Xiaohua Ma,^{2,3} and Yue Hao^{2,3}¹School of Advanced Materials and Nanotechnology, Xidian University, China, ²School of Microelectronics, Xidian University, China, ³Key Laboratory of Wide Band-Gap Semiconductor Technology, Xidian University, China*TuP-ED-7 (Poster)*

12:40 - 14:30

MOVPE-grown GaInN laser diodes with GaN tunnel junctionsRyosuke Iida,^{*}1 Kohei Miyoshi,² Yuki Kato,¹ Kei Arakawa,¹ Tetsuya Takeuchi,¹ Satoshi Kamiyama,¹ Motoaki Iwaya,¹ and Isamu Akasaki^{1,3}¹Meijo University, Japan, ²USHIO OPTO SEMICONDUCTORS, INC, Japan, ³Nagoya University, Japan*TuP-ED-8 (Poster)*

12:40 - 14:30

Migration Energies of 5-7 Edge Dislocations in GaNJesse Chiam Anderson,^{*}1 Masato Oda,^{1,2} Jun Nara,² and Tsuyoshi Miyazaki²¹Wakayama University, Japan, ²National Institute for Materials Science, Japan*TuP-ED-9 (Poster)*

12:40 - 14:30

The effects of PDA on the interface characteristics of GaN-based MIS-HEMTs in different atmosphere and temperatureSiyu Liu,^{*}1 Mi Ma,² Jielong Liu,¹ Fuchun Jia,² Qing Zhu,¹ Jiejie Zhu,^{1,2} Ling Yang,^{1,2} Xiaohua Ma,² and Yue Hao²¹School of Advanced Materials and Nanotechnology, Xidian University, China, ²State Key Discipline Laboratory of Wide BandGap Semiconductor Materials and Devices, School of Microelectronics, Xidian University, China*TuP-ED-10 (No Show)*

12:40 - 14:30

Comparison of device characteristics between recessed and regular AlGaIn/GaN SBDsGe Liu,^{*} Jincheng Zhang, Shenglei Zhao, Weihang Zhang, and Yue Hao

Key Laboratory of Wide Band Gap Semiconductor Materials and Devices, School of Microelectronics, Xidian University, China

TuP-ED-11 (Poster)

12:40 - 14:30

AlGaIn/GaN HFET with Thin AlGaIn Barrier Fabricated Using PECVD SiN_x PassivationHyun-Seop Kim,^{*1} Myoung-Jin Kang,² Won-Ho Jang,¹ Kwang-Seok Seo,² Hyungtak Kim,¹ Ho-Kyoung Lee,¹ Hyungsik Shin,¹ and Ho-Young Cha¹¹School of Electronic and Electrical Engineering, Hongik University, Republic of Korea, ²Department of Electrical and Computer Engineering, Seoul National University, Republic of Korea

TuP-ED-12 (Poster)

12:40 - 14:30

Temperature Dependence of Microwave Responsivity of Gated and Ungated Self-Switching Diodes Based on GaNJavier Mateos,^{*1} Elsa Pérez-Martín,¹ Héctor Sánchez-Martín,¹ Daniel Vaquero,¹ Gaudencio Paz,¹ José Antonio Novoa-López,¹ Susana Pérez,¹ Nicolas Defrance,² Christophe Gaquière,² Guillaume Ducournau,² Tomás González,¹ and Ignacio Íñiguez-de-la-Torre¹¹Universidad de Salamanca, Spain, ²IEMN, University of Lille 1, France

TuP-ED-13 (Poster)

12:40 - 14:30

Room temperature NDR in digital alloy AlGaIn barrier RTDsXinqiang Wang,^{*1} Ding Wang,^{1,2} Zhaoying Chen,¹ Tao Wang,¹ Wei Tan,³ Siping Guo,⁴ Jian Zhang,³ and Bo Shen²¹School of Physics, Peking University, China, ²Department of Engineering Physics, Tsinghua University, China, ³Microsystem and Terahertz Research Center, China, ⁴Advanced Micro-Fabrication Equipment Inc, China

TuP-ED-15 (No Show)

12:40 - 14:30

Hybrid Conductive Filaments Characteristic of the (In, N) co-doped ZnO Memory DeviceSih-Sian Li^{1,2} and Yan-Kuin Su^{*1,2}¹Institute of Microelectronics, Department of Electrical Engineering, Department of Photonics, National Cheng Kung University, Taiwan, ²Green Energy Technology Research Center, Department of Electrical Engineering, Kun Shan University, Taiwan

TuP-ED-16 (No Show)

12:40 - 14:30

Electrical and photocurrent properties of polycrystalline Sn-doped β -Ga₂O₃ thin film with thickness of 100 nmYounbgin Yoon,^{*1} Sunjae Kim,² In Gye Lee,² Byung Jin Cho,³ Myunghun Shin,¹ and Wan Sik Hwang²¹Department of Electronics and Information Engineering, Korea Aerospace University, Republic of Korea, ²Department of Materials Engineering, Korea Aerospace University, Republic of Korea, ³School of Electrical Engineering, KAIST, Republic of Korea

TuP-ED-17 (Poster)

12:40 - 14:30

Diamond SAW devices made by Minimal-fabAyano Nakasone,^{*1} Satoshi Fujii,¹ Sommawan Khumpuang,² Shiro Hara,² Haruki Toonoe,³ and Yasunori Shiba³¹National Institute of Technology, Okinawa College, Japan, ²AIIST, Japan, ³Yokogawa Solution Service, Japan

TuP-ED-18 (No Show)

12:40 - 14:30

Al₂O₃/TiO₂-Passivated In_{0.17}Al_{0.83}N/AlN/GaN Γ -Gate MOS-HFETsChing-Sung Lee,^{*1} Wei-Chou Hsu,² Yun-Jung Lin,¹ and Xue-Cheng Yao¹¹Department of Electronic Engineering, Feng Chia University, Taiwan, ²Institute of Microelectronics, National Cheng Kung University, Taiwan

TuP-ED-19 (Poster)

12:40 - 14:30

Flexible electrochromic transistorTakaki Onozato,^{*1} Hai Jun Cho,^{1,2} and Hiromichi Ohta^{1,2}¹Graduate School of Information Science and Technology (IST), Hokkaido University, Japan, ²Research Institute for Electronic Science (RIES), Hokkaido University, Japan

OD2 Visible & Novel Devices*Auditorium 14:40-15:55**Chair: Okhyun Nam and Baoping Zhang**OD2-1 (Invited)**14:40 - 15:10***Enhancement of LED Color Conversion Efficiency through Surface Plasmon Coupling**

Wen-Yen Chang, Yao-Tseng Wang, Cheng-Jin Cai, Rwei-Nan Wu, Chia-Chun Ni, Chun-Han Lin, Hsin-Chun Chiang, Yu-Feng Yao, Chi-Chung Chen, Wai Fong Tse, Yang Kuo, Yean-Woei Kiang, and Chih-Chung Yang*

*National Taiwan University, Taiwan**OD2-2 (Oral)**15:10 - 15:25***The Role of Surface Defects in Efficiency Degradation of GaInN-based Green Light-emitting Diodes**Dong-Pyo Han,^{*1} Seiji Ishimoto,¹ Ryoya Mano,¹ Weifang Lu,¹ Motoaki Iwaya,¹ Tetsuya Takeuchi,¹ Satoshi Kamiyama,¹ and Isamu Akasaki^{1,2}*¹Faculty of Science and Technology, Meijo University, Japan, ²Akasaki Research Center, Nagoya University, Japan**OD2-3 (Oral)**15:25 - 15:40***Demonstration of near-infrared light-emitting diodes with ultra-stable emission wavelength based on Tm-doped GaN**Naoki Yoshioka,^{*} Shuhei Ichikawa, Jun Tatebayashi, and Yasufumi Fujiwara*Division of Materials and Manufacturing Science, Graduate School of Engineering, Osaka University, Japan**OD2-4 (Oral)**15:40 - 15:55***The enhanced light output of ODR based UV-LEDs using porous SiO₂ layer**Jeong-won Lee^{*} and Tae-yeon Seong*Department of Nanophotonics Engineering, Korea University, Republic of Korea***CH1 Optical Characterization 1***Meeting Room 14:40-15:55**Chair: Bernard Gil and Atsushi A. Yamaguchi**CH1-1 (Invited)**14:40 - 15:10***New features of polar InGaN/GaN quantum wells and emitters induced by manipulation of built-in electric field**Tadek Suski,^{*1} Grzegorz Staszczak,¹ Grzegorz Muziol,¹ Krzysztof Korona,² Anna Kafar,^{1,4} Szymon Stanczyk,¹ Czeslaw Skierbiszewski,^{1,3} and Piotr Perlin^{1,3}*¹Institute of High Pressure Physics, Polish Academy of Sciences, Poland, ²Institute of Experimental Physics, Warsaw University, Poland,**³TopGaN Ltd., Poland, ⁴Kyoto University, Japan**CH1-2 (Oral)**15:10 - 15:25***Origin and dynamic properties of intrinsic nonradiative recombination centers in bulk and epitaxial ZnO**Shigefusa F. Chichibu,^{*1} Kazunobu Kojima,¹ Kazuto Koike,² Mitsuaki Yano,² Shun-ichi Gonda,³ Shoji Ishibashi,⁴ and Akira Uedono⁵*¹Tohoku University, Japan, ²Osaka Institute of Technology, Japan, ³Osaka University, Japan, ⁴National Institute of Advanced Industrial Science and Technology, Japan, ⁵University of Tsukuba, Japan*

CHI-3 (Oral)

15:25 - 15:40

Red emission enhancement from InGaN using nanocolumn plasmonic crystals with honeycomb and kagome latticesAoto Aihara,^{*}¹ Kazuma Kikuchi,² Koichi Okamoto,⁴ Rie Togashi,² Katsumi Kishino,³ and Takao Oto¹¹Yamagata University, Japan, ²Sophia University, Japan, ³Sophia Nanotechnology Research Center, Japan, ⁴Osaka Prefecture University, Japan

CHI-4 (Oral)

15:40 - 15:55

High-temperature promoted nonradiative recombination at threading dislocations in blue-emitting InGaN quantum wellRyota Ishii,^{*} Yuji Koyama, Mitsuru Funato, and Yoichi Kawakami

Department of Electronic Science and Engineering, Kyoto University, Japan

Break

15:55 - 16:25

OD3 UV Devices 1

Auditorium 16:25-17:55

Chair: Xinqiang Wang and Tim Wernicke

OD3-1 (Invited)

16:25 - 16:55

Toward the realization of AlGaIn-based UVB laser diodesMotoaki Iwaya,^{*}¹ Kosuke Sato,^{1,2} Sho Iwayama,^{1,3} Tetsuya Takeuchi,¹ Satoshi Kamiyama,¹ Isamu Akasaki,^{1,4} and Hideto Miyake³¹Department of Materials Science and Engineering, Meijo Univ., Japan, ²Asahi-Kasei Corporation, Japan, ³Graduate School of Regional Innovation Studies, Mie University, Japan, ⁴Akasaki Research Center, Nagoya University, Japan

OD3-2 (Invited)

16:55 - 17:25

A pathway toward low threshold UVC laser diodesZlatko Sitar,^{*}^{1,2} Ronny Kirste,² Seiji Mita,² Pramod Reddy,² Qiang Guo,¹ Biplab Sarkar,¹ Doug Irving,¹ and Ramon Collazo¹¹North Carolina State University, United States of America, ²Adroit Materials, United States of America

OD3-3 (Oral)

17:25 - 17:40

42mW light power from AlGaIn-based 302nm-band UVB LEDs: a way forward for UVB LDsMuhammad Ajmal Khan,^{*}^{1,2} Noritoshi Maeda,¹ Masafumi Jo,¹ Sachie Fujikawa,^{1,4} Yoichi Yamada,³ and Hideki Hirayama Hirayama^{1,2}¹RIKEN Center for Advanced Photonics (RAP), Japan, ²RIKEN Cluster for Pioneering Research, Japan, ³Faculty of Engineering, Yamaguchi University, Japan, ⁴Tokyo Denki University, Japan

OD3-4 (Oral)

17:40 - 17:55

High performance of AlGaIn deep-ultraviolet light emitting diodes due to improved vertical carrier transport by delta-accelerating quantum barriersJing Lang,^{*} Fujun Xu, Weikun Ge, Baiyin Liu, Na Zhang, Yuanhao Sun, Jiaming Wang, Mingxing Wang, Nan Xie, and Bo Shen

Peking University, China

CH2 Extended Defects

Meeting Room 16:25-17:55

Chair: Akira Sakai and Bo Shen

CH2-1 (Invited)

16:25 - 16:55

Control and annihilation of dislocation propagation in diamond by metal-assisted termination

Shinya Ohmagari,* Hideaki Yamada, Nobuteru Tsubouchi, Hitoshi Umezawa, Akiyoshi Chayahara, and Daisuke Takeuchi
National Institute of Advanced Industrial Science and Technology, Japan

CH2-2 (Invited)

16:55 - 17:25

Nondestructive defect characterization of widegap semiconductors using multiphoton-excitation photoluminescence

Tomoyuki Tanikawa,* Masahiro Uemukai, and Ryuji Katayama
Osaka University, Japan

CH2-3 (Oral)

17:25 - 17:40

Vacancy assistant dislocation engineering for continuous 10.2 μm -thick GaN films on Si substrates

Jie Zhang, Xuelin Yang,* Jianfei Shen, and Bo Shen
School of Physics, Peking University, China

CH2-4 (Oral)

17:40 - 17:55

Defect structure analysis of OVPE grown homoepitaxial GaN thick film

Tetsuya Tohei,*¹ Miki Manabe,¹ Junichi Takino,² Tomoaki Sumi,² Masayuki Imanishi,³ Yusuke Mori,³ and Akira Sakai¹
¹Graduate School of Engineering Science, Osaka University, Japan, ²Panasonic Corporation, Japan, ³Graduate School of Engineering, Osaka University, Japan

November 13 (Wednesday)

GR4 Novel Process Technology

Auditorium 09:00-10:45

Chair: Motoaki Iwaya and Chih-Chung Yang

GR4-1 (Invited)

09:00 - 09:30

Threading Dislocation Reduction of Sputter-deposited AlN/sapphire by High-Temperature Annealing

Hideto Miyake,^{*1,2} Kenjiro Uesugi,^{1,3} Kanako Shojiki,² Shiyu Xiao,¹ Haruhiko Koizumi,³ and Shigeyuki Kuboya³

¹Graduate School of Regional Innovation Studies, Mie University, Japan, ²Graduate School of Engineering, Mie University, Japan,

³Organization for Promotion of Regional Innovation, Mie University, Japan

GR4-2 (Invited)

09:30 - 10:00

Growth and characterization of widegap III-nitride based optoelectronic and electronic devices using HT-MOCVD

Okhyun Nam

Korea Polytechnic University, Republic of Korea

GR4-3 (Oral)

10:00 - 10:15

Enhanced doping efficiency of p-GaN grown on free standing GaN substrates

liwen sang,^{*} Bing Ren, Raimu Endo, Takuya Masuda, Toshihide Nabatame, Masatomo Sumiya, Yasuo Koide, and Meiyong Liao

National Institute for Materials Science, Japan

GR4-4 (Oral)

10:15 - 10:30

Carbon and aluminum co-treatment at high temperatures for surface p-type conduction of AlN

Katsuhiko Kishimoto,^{*} Mitsuru Funato, and Yoichi Kawakami

Department of Electronic Science and Engineering, Kyoto University, Japan

GR4-5 (Oral)

10:30 - 10:45

Highly controllable self-assembled AlGaIn-quantum wires grown on sapphire with large mis-cut angle

Yuanhao Sun,^{*} Fujun Xu, Mingxing Wang, Jing Lang, Na Zhang, and Bo Shen

State Key Laboratory of Artificial Microstructure and Mesoscopic Physics, School of Physics, Peking university, China

ED3 Novel Electronic Devices

Meeting Room 09:00-10:45

Chair: Masataka Higashiwaki and Nam Kyun Kim

ED3-1 (Invited)

09:00 - 09:30

Recent progress for inversion channel mobility improvement in diamond MOSFETs

Tsubasa Matsumoto,^{*1} Ukyo Sakurai,³ Tomoya Yamakawa,³ Hiromitsu Kato,² Toshiharu Makino,² Masahiko Ogura,² Daisuke Takeuchi,² Satoshi Yamasaki,^{1,2} Takao Inokuma,² and Norio Tokuda^{1,2}

¹Nanomaterials Research Institute, Kanazawa University, Japan, ²Advanced Power Electronics Research Center, AIST, Japan, ³Graduate School of Natural Science and Technology, Kanazawa University, Japan

ED3-2 (Invited)

09:30 - 10:00

Ga₂O₃ Power Device Potential Investigation Based on Its Nano-membrane ChannelsHong Zhou,* Jincheng Zhang, and Yue Hao
Xidian University, China

ED3-3 (Oral)

10:00 - 10:15

Very high sensitive AlGaIn/GaN HEMT sensor for hydrogen detection at room temperatureKyung-Ho Park,* Chu-Young Cho, Hae-Yong Jeong, Hyeong-Ho Park, Jeong-Min Ju, and Young-Jae Jo
Devices Technology Division, Korea Advanced Nano Fab Center (KANC), Republic of Korea

ED3-4 (Oral)

10:15 - 10:30

Significant Image Force Lowering at Metal/Heavily-Doped SiC InterfacesMasahiro Hara,* Satoshi Asada, Takuya Maeda, and Tsunenobu Kimoto
Department of Electronic Science and Engineering, Kyoto University, Japan

ED3-5 (Oral)

10:30 - 10:45

Lateral GaN SBD for 5.8GHz Microwave Rectifier with A Peak Efficiency of 71% at Input Power of 33.96 dBmKui Dang,* Jincheng Zhang, Hong Zhou, and Yue Hao
Xidian University, China

Break

10:45 - 11:15

OD4 MicroLED

Auditorium 11:15-13:00

Chair: Jen-Inn Chyi and Jinmin Li

OD4-1 (Invited)

11:15 - 11:45

Development of Transparent MicroLED DisplayYing-Tsang Liu, Kuan-Yung Liao, Yu-Hung Lai, and Yun-Li Li*
PlayNitride Inc., Taiwan

OD4-2 (Invited)

11:45 - 12:15

GaN-based integrated micro LED researchKei May Lau
Department of Electronic and Computer Engr., Hong Kong U. of Science & Technology, Hong Kong

OD4-3 (Oral)

12:15 - 12:30

Fabrication of Needle-Shaped GaN- μ LED Neural Probe for OptogeneticsHiroki Yasunaga,*¹ Masahiro Ohsawa,² and Hiroto Sekiguchi^{1,3}
¹Toyohashi Tech, Japan, ²Nagoya city Univ., Japan, ³JST PRESTO, Japan

OD4-5 (Oral)

12:45 - 13:00

Integration of GaN LED and Si-CMOS on 200 mm Si PlatformLi Zhang,*¹ Kwang Hong Lee,¹ Kenneth Lee,¹ Chuan Seng Tan,^{1,2} Soo Jin Chua,^{1,3} and Eugene A. Fitzgerald^{1,4}
¹Singapore-MIT Alliance for Research and Technology, Singapore, ²School of Electrical and Electronic Engineering, Nanyang Technological University, Singapore, ³Department of Electrical and Computer Engineering, National University of Singapore, Singapore, ⁴Department of Materials Science and Engineering, Massachusetts Institute of Technology, United States of America

CH3 Optical Characterization 2

Meeting Room 11:15-13:00

Chair: Yoshihiro Ishitani and Tadek Suski

CH3-1 (Invited)

11:15 - 11:45

Phonons, free charge carriers, excitons and band-to-band transitions in beta Ga₂O₃ and related alloys determined by ellipsometry and optical Hall effect

M. Schubert,^{*,1,2,3} A. Mock,⁴ S. Knight,¹ M. Hilfiker,¹ M. Stokey,¹ V. Darakchieva,² A. Papamichail,² R. Korlacki,¹ M.J. Tadjer,⁵ Z. Galazka,⁶ G. Wagner,⁶ N. Blumenschein,⁷ A. Kuramata,⁸ K. Goto,^{8,9} H. Murakami,⁹ Y. Kumagai,⁸ M. Higashiwaki,¹⁰ A. Mauze,¹⁰ Y. Zhang,¹¹ and J. S. Speck¹¹

¹Department of Electrical and Computer Engineering, University of Nebraska, United States of America, ²Department of Physics, Chemistry and Biology (IFM), Linköping University, Sweden, ³Leibniz Institute for Polymer Research, Germany, ⁴National Research Council Postdoctoral Fellow, residing at U.S. Naval Research Laboratory, United States of America, ⁵U.S. Naval Research Laboratory Electronics Science and Technology Division, United States of America, ⁶Leibniz-Institut für Kristallzüchtung, Germany, ⁷Department of Electrical and Computer Engineering, North Carolina State University, United States of America, ⁸Novel Crystal Technology, Inc., Japan, ⁹Department of Applied Chemistry, Tokyo University of Agriculture and Technology, Japan, ¹⁰National Institute of Information and Communications Technology, Japan, ¹¹Materials Department, University of California Santa Barbara, United States of America

CH3-2 (Invited)

11:45 - 12:15

Deep UV cathodoluminescence properties of rocksalt-structured MgZnO alloys

Takeyoshi Onuma,^{*,1} Mizuki Ono,¹ Kanta Kudo,¹ Kyohei Ishii,² Kentaro Kaneko,^{2,3,4} Shizuo Fujita,^{2,4} and Tohru Honda¹

¹Department of Applied Physics and Graduate School of Engineering, Kogakuin University, Japan, ²Department of Electronic Science and Engineering, Kyoto University, Japan, ³Engineering Education Research Center, Kyoto University, Japan, ⁴Photonics and Electronics Science and Engineering Center, Kyoto University, Japan

CH3-3 (Oral)

12:15 - 12:30

Luminescence enhancement of N-polar InGaN/GaN multiple quantum wells grown by flow modulation epitaxy

Chengguo Li

Guangdong Institute of Semiconductor Industrial Technology, China

CH3-4 (Oral)

12:30 - 12:45

Radiative and Nonradiative Recombination Rates of Excitons and Their Effects on Internal Quantum Efficiency of AlGaIn-based UV-B MQWs

Hideaki Murotani,^{*,1,2} Hiroyuki Miyoshi,¹ Ryohei Takeda,¹ Muhammad Ajmal Khan,³ Noritoshi Maeda,³ Masafumi Jo,³ Hideki Hirayama,³ and Yoichi Yamada¹

¹Department of Electrical and Electronic Engineering, Yamaguchi University, Japan, ²National Institute of Technology, Tokuyama College, Japan, ³RIKEN Cluster for Pioneering Research, Japan

CH3-5 (Oral)

12:45 - 13:00

Simulation and growth of GaN/AlGaIn based terahertz quantum cascade structures

Ke Wang,^{*,1,2} Li Wang,² Tsung-Tse Lin,² Koichi Fukuda,² Rong Zhang,¹ and Hideki Hirayama²

¹School of Electronic Science and Engineering, Nanjing University, China, ²Terahertz Quantum Device team, RAP, RIKEN, Japan

Excursion

13:00 - 18:00

*November 14 (Thursday)***OD5 UV Devices 2***Auditorium 09:00-10:15**Chair: Ryota Ishii and Ke Wang**OD5-1 (Invited)**09:00 - 09:30***Emerging new techniques for efficient AlGa_N DUV LEDs: from 2D to 3D**

Jinmin Li

*Institute of Semiconductors, Chinese Academy of Science, China**OD5-2 (Invited)**09:30 - 10:00***Prospects and challenges for UV LEDs and UV lasers with tunnel junctions**Tim Wernicke,^{*} Luca Sulmoni,¹ Martin Guttmann,¹ Norman Susilo,¹ Eviathar Ziffer,¹ Christian Kuhn,¹ Frank Mehnke,¹ Anton Muhin,¹ Filip Hjort,² Johannes Enslin,¹ Munise Cobet,^{1,3} Michael A. Bergmann,² Martin Martens,¹ Johan Gustavsson,² Åsa Haglund,² and Michael Kneissl^{1,4}¹*Technical University of Berlin, Germany, 2Chalmers University of Technology, Sweden, 3Johannes Kepler University Linz, Austria, 4Ferdinand-Braun-Institut, Germany**OD5-3 (Oral)**10:00 - 10:15***High current operation of UV-B devices fabricated on low dislocation and relaxed AlGa_N**Shinji Yasue,^{*} Kosuke Sato,^{1,2} Yusuke Sakuragi,¹ Yuya Ogino,¹ Syunya Tanaka,¹ Shohei Teramura,¹ Sho Iwayama,^{1,4} Motoaki Iwaya,¹ Takeuchi Tetsuya,¹ Satoshi Kamiyama,¹ Isamu Akasaki,^{1,3} and Hideto Miyake⁴¹*Department of Materials Science and Engineering, Meijo University, Japan, 2Asahi-Kasei Corporation, Japan, 3Akasaki Research Center, Nagoya University, Japan, 4Graduate School of Regional Innovation Studies, Mie University, Japan***GR5 Bulk Growth***Meeting Room 09:00-10:15**Chair: Yusuke Mori and Zlatko Sitar**GR5-1 (Invited)**09:00 - 09:30***Acidic Ammonothermal Growth of Bulk GaN**Yutaka Mikawa,^{*} Takayuki Ishinabe, Yuji Kagamitani, Hirotaka Ikeda, and Tae Mochizuki*Mitsubishi Chemical Corporation, Japan**GR5-2 (Invited)**09:30 - 10:00***Bulk growth of GaN. How to overcome the equilibrium crystal shape?**

Michal Stanislaw Bockowski

¹*IHPP PAS, Poland, 2CIRFE, IMASS, Nagoya University, Japan**GR5-3 (Oral)**10:00 - 10:15***GaN crystal growth by basic ammonothermal method**Guoqiang Ren,^{*} Tengkun Li,¹ Xujun Su,¹ Jingjing Yao,¹ Xiaodong Gao,¹ and Ke Xu^{1,2}¹*Suzhou Institute of Nano-tech and Nano-bionics, Chinese Academy of Sciences, China, 2Suzhou Nanowin Science and Technology Co, Ltd., China**Break**10:15 - 10:45*

ED4 Power Devices

Auditorium 10:45-12:30

Chair: Shinsuke Harada and Chih-Fang Huang

ED4-1 (Invited)

10:45 - 11:15

Development of SiC power devices with low on-resistance

Nam Kyun KIM

Korea Electrotechnology Research Institute (KERI), Republic of Korea

ED4-2 (Invited)

11:15 - 11:45

Dynamic Performance and Surge Current Capability of Vertical GaN-on-GaN Power Devices

Shu Yang,* Shaowen Han, and Kuang Sheng

College of Electrical Engineering, Zhejiang University, China

ED4-3 (Oral)

11:45 - 12:00

Impacts of Channel Length on Electrical Characteristics in Side-Gate SiC JFETs

Masashi Nakajima,* Qimin Jin, Mitsuaki Kaneko, and Tsunenobu Kimoto

Kyoto University, Japan

ED4-4 (Oral)

12:00 - 12:15

Investigation of thin-AlGaIn/GaN MOS-HFETs on the AlGaIn back-barrier structure for normally-off operation

Jumpei Tajima,* Toshiki Hikosaka, and Shinya Nunoue

Corporate Research & Development Center, Toshiba Corporation, Japan

ED4-5 (Oral)

12:15 - 12:30

Depth Profiles of Defects Generated by RIE in 4H-SiC Characterized by Deep-level Transient Spectroscopy

Kazutaka Kanegae,*¹ Takafumi Okuda,¹ Masahiro Horita,^{1,2} Jun Suda,^{1,2} and Tsunenobu Kimoto¹

¹Kyoto Univ., Japan, ²Nagoya Univ., Japan

CH4 Physical Properties

Meeting Room 10:45-12:30

Chair: Frank Bertram and Shigefusa F. Chichibu

CH4-1 (Invited)

10:45 - 11:15

Boron nitride from its physics to advanced photonic applications

Bernard GIL

CNRS & University Montpellier, France

CH4-2 (Oral)

11:15 - 11:30

Electrical spin injection into bulk GaN with Co/MgO spin injector

Xingchen liu,¹ Ning Tang,*¹ C. Fang,² Xiaoyue Zhang,¹ Hongming Guan,¹ Yunfan Zhang,¹ C.H Wan,² Weikun Ge,¹ X.F Han,² and Bo Shen¹

¹State Key Laboratory of Artificial Microstructure and Mesoscopic Physics, School of Physics, Peking University, China, ²Beijing National Laboratory for Condensed Matter Physics, Institute of Physics, University of Chinese Academy of Sciences, Chinese Academy of Sciences, China

CH4-3 (Oral)

11:30 - 11:45

RF sputtering deposition of Mg-doped h-BN films on Al_{0.7}Ga_{0.3}N templateGUODONG HAO,* Manabu Taniguchi, Sachiko Tsuzuki, and Shin-ichiro Inoue
National Institute of Information and Communications Technology (NICT), Japan

CH4-4 (Oral)

11:45 - 12:00

Energy distributions of interface state density originating from tail states of the conduction band in SiC MOS structuresKoji Ito,* Takuma Kobayashi, and Tsunenobu Kimoto
Kyoto University, Japan

CH4-5 (Oral)

12:00 - 12:15

Zn-IV-nitrides for integration in electronic and photonic devicesNicholas Lloyd Adamski,*¹ Darshana Wickramaratne,² and Chris G. Van de Walle³¹Department of Electrical and Computer Engineering, University of California, Santa Barbara, United States of America, ²US Naval Research Laboratory, United States of America, ³Materials Department, University of California, Santa Barbara, United States of America

CH4-6 (Oral)

12:15 - 12:30

In-situ observation of stacking faults expansion in 4H-SiC at high temperatures by synchrotron X-ray topographyFumihiko Fujie,*¹ Shunta Harada,¹ Hiromasa Suo,² Tomohisa Kato,³ and Toru Ujihara¹¹Nagoya University, Japan, ²Showa Denko K.K., Japan, ³National Institute of Advanced Industrial Science and Technology (AIST), Japan**Poster Poster Session C**

Tunnel Gallery 12:30-14:20

ThP-GR-1 (Poster)

12:30 - 14:20

In-plane misfits' localization in GaN via graphene-ELOG technologyYu Xu,*^{1,2} Xujun Su,¹ Bing Cao,^{3,4} Zongyao Li,² Yi Liu,^{3,4} Demin Cai,² Yumin Zhang,^{1,2} Jianfeng Wang,^{1,2} Chinhua Wang,^{3,4} and Ke Xu^{1,2}¹Suzhou Institute of Nano-Tech and Nano-Bionics (SINANO), Chinese Academy of Sciences (CAS), Suzhou 215123, China, ²Suzhou Nanowin Science and Technology Co., Ltd., Suzhou 215123, China, ³School of Optoelectronic Science and Engineering & Collaborative Innovation Center of Suzhou Nano Science and Technology, Soochow University, Suzhou 215006, China, ⁴Key Lab of Advanced Optical Manufacturing Technologies of Jiangsu Province & Key Lab of Modern Optical Technologies of Education Ministry of China, Soochow University, Suzhou 215006, China

ThP-GR-2 (Poster)

12:30 - 14:20

Study on p-GaN shell in nanowire core-shell LEDNanami Goto,*¹ Naoki Sone,^{1,2} Kazuyoshi Iida,^{1,3} Weifang Lu,¹ Hideki Murakami,¹ Mizuki Terazawa,¹ Jun Uzuhashi,⁴ Tadakatsu Ohkubo,⁴ Kazuhiro Hono,⁴ Masaki Ohya,^{1,3} Satoshi Kamiyama,¹ Tetsuya Takeuchi,¹ Motoaki Iwaya,¹ and Isamu Akasaki^{1,5}¹Meijo University, Japan, ²Koito Manufacturing CO., Ltd, Japan, ³Toyada Gosei Co., Ltd, Japan, ⁴National Institute for Materials Science, Japan, ⁵Akasaki Research Center, Nagoya Univ., Japan

ThP-GR-3 (Poster)

12:30 - 14:20

Theoretical Study of the Origins of Carbon Impurities on GaN MOVPE from a Gas Phase Reaction Perspective ~Incorporation of Ga and C Related Molecules~Yuto Okawachi,*¹ Kenta Chokawa,¹ Masaaki Araidai,² Akira Kusaba,⁴ Yoshihiro Kangawa,^{2,3} Koichi Kakimoto,³ Zheng Ye,¹ Yoshio Honda,^{1,2} Shugo Nitta,^{1,2} Hiroshi Amano,^{1,2} and Kenji Shiraiishi^{1,2}¹Graduate School of Engineering, Nagoya Univ, Japan, ²ImaSS, Nagoya Univ, Japan, ³RIAM, Kyushu Univ, Japan, ⁴Computer Center, Gakushuin Univ, Japan

ThP-GR-4 (Poster)

12:30 - 14:20

Numerical Modeling of Carbon Doping and Experimental Validation in GaN Epitaxial Growth by MOVPE methodMasaya Iizuka,^{*}¹ Yuji Mukaiyama,¹ A. V. Lobanova,² R. A. Talalaev,² and W. Lundin³¹STR Japan K.K, Japan, ²STR Group - Soft Impact Ltd, Russia, ³Ioffe Physical Technical Institute, Russia

ThP-GR-5 (Poster)

12:30 - 14:20

Effect of temperature gradient on AlN crystal growth by PVT methodLei Zhang,^{*}¹ Guodong Wang,¹ Yong Wang,¹ Yongliang Shao,¹ Chengmin Chen,² Yongzhong Wu^{*},¹ and Xiaopeng Hao^{*}¹¹State Key Lab of Crystal Materials, Shandong University, China, ²Energy Research Institute, Qilu University of Technology (Shandong Academy of Sciences), China

ThP-GR-6 (Poster)

12:30 - 14:20

Realization of p-type gallium nitride by magnesium ion implantationYating Shi,^{*} Weizong Xu, Xuanhu Chen, Fangfang Ren, Dong Zhou, Jiandong Ye, Dunjun Chen, Rong Zhang, Youdou Zheng, and Hai Lu

School of Electronic Science and Engineering, Nanjing University, China

ThP-GR-7 (Poster)

12:30 - 14:20

3-inch Homogeneous GaN Single Crystal Grown by Na Flux MethodZong-liang Liu,^{*}¹ Hong Gu,¹ Xiao-ming Dong,¹ Guo-qiang Ren,¹ Jian-feng Wang,^{1,2} and Ke Xu^{1,2}¹Suzhou Institute of Nano-tech and Nano-bionics, CAS, China, ²Suzhou Nanowin Science and Technology Co., Ltd., China

ThP-GR-8 (Poster)

12:30 - 14:20

In-situ observation of AlN crystal growth on Fe-Al meltsTakefumi Yamagata,^{*} Masayoshi Adachi, and Hiroyuki Fukuyama

Institute of Multidisciplinary Research for Advanced Materials (IMRAM), Tohoku University, Japan

ThP-GR-9 (Poster)

12:30 - 14:20

GaN growth on SiC buffer layer formed by carbonization on Si substratesYifu Zhu,^{*} Jianwei Wang, Takeshi Momose, Yukihiro Shimogaki, and Momoko Deura

The University of Tokyo, Japan

ThP-GR-10 (Poster)

12:30 - 14:20

Laser slicing techniques for cutting out GaN substrateAtsushi Tanaka,^{*}^{1,2} Yasunori Igasaki,¹ and Hiroshi Amano^{1,2,3,4}¹Institute of Materials and Systems for Sustainability, Nagoya University, Japan, ²National Institute for Materials Science, Japan, ³Akasaki Research Center, Japan, ⁴Venture Business Laboratory, Japan

ThP-GR-11 (Poster)

12:30 - 14:20

Optical characterization of GaN-QPM crystal fabricated by DP-SAG in MOVPEKai Matsuhisa,^{*}¹ Yuto Kobayashi,¹ Hiroki Ishihara,¹ Mako Sugiura,¹ Atsushi Sugita,¹ Yoku Inoue,¹ and Takayuki Nakano^{1,2}¹Shizuoka Univ., Japan, ²R.I.E. Shizuoka Univ., Japan

ThP-GR-12 (Poster)

12:30 - 14:20

Investigation of AlGaN/AlN interface structure and annealing effect for control of strain relaxationYuri Itokazu,^{*}^{1,2} Shunsuke Kuwaba,^{1,2} Jo Masafumi,¹ Norihiko Kamata,² and Hideki Hirayama¹¹RIKEN, Japan, ²Department of Functional Materials Science, Saitama University, Japan

ThP-GR-13 (Poster)

12:30 - 14:20

Analysis of Solution Structure in Solution growth of SiC with Na fluxTakuro Murata* and Takahiro Kawamura
*Graduate School of Engineering, Mie University, Japan**ThP-GR-14 (Poster)*

12:30 - 14:20

Solid Phase Epitaxy of AB₂O₄ Complex Oxides: ZnGa₂O₄ as an ExamplePo-Wei Chen, Shiau-Yuan Huang, Shuo-Huang Yuan, and Dong-Sing Wu*
*Department of Materials Science and Engineering, National Chung Hsing University, Taiwan**ThP-GR-15 (Poster)*

12:30 - 14:20

Influence of substrate constraint on the emergence of metastable α -Ga₂O₃Chika Ohashi,*¹ Takashi Kamo,¹ Ryo Miura,¹ Nao Takekawa,¹ Rie Togashi,² Ken Goto,¹ and Yoshinao Kumagai^{1,3}
¹*Department of Applied Chemistry, Tokyo University of Agriculture and Technology, Japan,* ²*Department of Engineering and Applied Sciences, Sophia University, Japan,* ³*Institute of Global Innovation Research, Tokyo University of Agriculture and Technology, Japan**ThP-GR-16 (Poster)*

12:30 - 14:20

Growth Control of α -Ga₂O₃ Thin Films using Chloride-Based Gallium Source Solutions in Mist Chemical Vapor DepositionKazuyuki Uno,* Kazutoshi Matsumoto, and Ichiro Tanaka
*Wakayama University, Japan**ThP-GR-17 (Poster)*

12:30 - 14:20

Carrier density control of epitaxial NiO thin films grown using mist CVD methodTakumi Ikenoue,* Masao Miyake, and Tetsuji Hirato
*Graduate School of Energy Science, Kyoto University, Japan**ThP-CH-2 (No Show)*

12:30 - 14:20

Studies on Internal Quantum Efficiency and Carrier Dynamics of AlGa_N Ultraviolet Radiation B introduced by Lateral-Polarity StructureYingda Qian,*¹ Wei Guo,² Kaiyan He,¹ and Zhe Chuan FENG¹
¹*School of Physical Science & Technology, Guangxi University, China,* ²*Ningbo Institute of Materials Technology and Engineering (NIMTE), Chinese Academy of Sciences, China**ThP-CH-4 (Poster)*

12:30 - 14:20

InGa_N single quantum well intersected by individual dislocationsGordon Schmidt, Frank Bertram,* Peter Veit, Sebastian Metzner, Christoph Berger, Armin Dadgar, André Strittmatter, and Jürgen Christen
*Institute of Physics, Otto-von-Guericke-University Magdeburg, Germany**ThP-CH-5 (Poster)*

12:30 - 14:20

Unfolding band structures of BAlN and BGa_N alloysYuichi Ota
*Tokyo Metropolitan Industrial Technology Research Institute, Japan**ThP-CH-6 (Poster)*

12:30 - 14:20

Engineering of emission wavelength of InGa_N quantum wells by fabrication of spatial off-cut variationAnna Kafar,*^{1,2} Ryota Ishii,¹ Szymon Stanczyk,² Krzysztof Gibasiewicz,² Szymon Grzanka,^{2,3} Tadeusz Suski,² Piotr Perlin,^{2,3} Mitsuru Funato,¹ and Yoichi Kawakami¹
¹*Kyoto University, Japan,* ²*Institute of High Pressure Physics PAS, Poland,* ³*TopGa_N Ltd., Poland*

ThP-CH-7 (Poster)

12:30 - 14:20

Active Efficiency as an Effective Quality Indicator for the Active Layer of Light-Emitting DiodesChan-Hyoung Oh,¹ Jong-In Shim,^{*,2} Dong-Soo Shin,^{2,3} and Hyundon Jung⁴¹Department of Electronics and Communication Engineering, Hanyang University ERICA, Republic of Korea, ²Department of Photonics and Nanoelectronics, Hanyang University ERICA, Republic of Korea, ³ Department of Bionanotechnology, Hanyang University ERICA, Republic of Korea, ⁴EtaMax Co. Ltd., Republic of Korea

ThP-CH-8 (Poster)

12:30 - 14:20

Influence of the growth direction for SCAATTM on annealing effectsKenji Iso,^{*} Yutaka Mikawa, Hirotaka Ikeda, Kazuriho Hotta, Tae Mochizuki, and Satoru Izumisawa
Mitsubishi Chemical, Japan

ThP-CH-9 (Poster)

12:30 - 14:20

Fabrication of GaN nanowires by wet processes using electrodeless photo-assisted electrochemical etching and alkaline solution treatmentMichihito Shimauchi,^{*,1,2} Kazuki Miwa,¹ Masachika Toguchi,^{1,2} Taketomo Sato,¹ and Junichi Motohisa²¹Research Center for Integrated Quantum Electronics, Hokkaido University, Japan, ²Graduate School of Information Science and Technology, Hokkaido University, Japan

ThP-CH-10 (Poster)

12:30 - 14:20

Microscopic analysis of heat transport at GaInN/GaN heterointerface with misfit dislocations by two-wavelength Raman measurementsShungo Okamoto,¹ Bei Ma,¹ Ken Morita,¹ Daisuke Iida,² Kazuhiro Ohkawa,² and Yoshihiro Ishitani^{*,1}¹Chiba University, Japan, ²King Abdullah University of Science and Technology, Saudi Arabia

ThP-CH-12 (Poster)

12:30 - 14:20

Size-dependent optical characteristics of single InGaN quantum wire grown on c-plane GaN template by MOCVDHwan-Seop Yeo,^{*,1} Kwanjae Lee,¹ Young Chul Sim,¹ Seoung-Hwan Park,² and Yong-Hoon Cho¹¹Department of Physics, Korea Advanced Institute of Science and Technology (KAIST), Republic of Korea, ²Department of Electronics Engineering, Catholic University of Daegu, Republic of Korea

ThP-CH-13 (Poster)

12:30 - 14:20

Impact of high-temperature nitrogen annealing on interface properties of p-type 4H-SiC/SiO₂Keita Tachiki,^{*} Kazutaka Kanegae, and Tsunenobu Kimoto
Kyoto University, Japan

ThP-CH-14 (Poster)

12:30 - 14:20

Investigation of Etching Characteristics of HVPE-Grown In₂O₃ Layers by Hydrogen-Environment Anisotropic Thermal EtchingRyo Kasaba,^{*,1} Yuki Ooe,¹ Kenta Nagai,² Ken Goto,² Rie Togashi,¹ Akihiko Kikuchi,¹ and Yoshinao Kumagai²¹Department of Engineering and Applied Sciences, Sophia University, Japan, ²Department of Applied Chemistry, Tokyo University of Agriculture and Technology, Japan

ThP-CH-15 (No Show)

12:30 - 14:20

The Change of Band Gap Energy for the WS_xSe_y MonolayerYung-Huang Chang,^{*,1} Yuan-Tsung Chen,² Chien-Sheng Huang,³ and Cheng-Jia Tang³¹Bachelor Program in Interdisciplinary Studies, National Yunlin University of Science and Technology, Taiwan, ²Graduate School of Materials Science, National Yunlin University of Science and Technology, Taiwan, ³Department of Electronic Engineering, National Yunlin University of Science and Technology, Taiwan

ThP-OD-1 (Poster)

12:30 - 14:20

Light Emitting Characteristics of P-GaN on $\text{Al}_{0.32}\text{Ga}_{0.68}\text{N}/\text{Al}_{0.07}\text{Ga}_{0.93}\text{N}$ HEMT

Chih-Yao Chang,* Jun-Lin Wu, and Chih-Fang Huang

Institute of Electronics Engineering, National Tsing Hua University, Taiwan

ThP-OD-2 (Poster)

12:30 - 14:20

Development of Chip-Scale Package GaN-Based Light-Emitting Diodes with Varistor-embedded Ceramic SubstrateByongjin Ma,*¹ Kwanhun Lee,¹ Young Jun An,² and Kyung-Whan Woo²¹*Korea Electronics Technology Institute (KETI), Republic of Korea,* ²*Amosense Co. Ltd., Republic of Korea*

ThP-OD-3 (Poster)

12:30 - 14:20

Excitation dynamics and efficiency of luminescence of Eu in GaNDolf Timmerman,*¹ Masaaki Ashida,² and Yasufumi Fujiwara¹¹*Graduate School of Engineering, Osaka University, Japan,* ²*Graduate School of Engineering Science, Osaka University, Japan*

ThP-OD-4 (Poster)

12:30 - 14:20

Enhanced Resonance of Luminescence in GaN-based Square Microdisks

Menghan Liu,* Peng Chen, Ru Xu, Jing Zhou, Yimeng Li, Cheng Ge, Haocheng Peng, Xiaokang Mao, Zili Xie, Bin Liu, Rong Zhang, and Youdou Zheng

Jiangsu Provincial Key Laboratory of Advanced Photonic and Electronic Materials, School of Electronic Science and Engineering, Nanjing University, China

ThP-OD-5 (Poster)

12:30 - 14:20

Blue light hazard optimization for multi-chip dynamic white light emitting diodes with high color fidelityJingxin Nie,*¹ Zhizhong Chen,¹ and Fei Jiao^{1,2}¹*State Key Laboratory for Artificial Microstructure and Mesoscopic Physics, School of Physics, Peking University, China,* ²*State Key Laboratory of Nuclear Physics and Technology, School of Physics, Peking University, China*

ThP-OD-6 (Poster)

12:30 - 14:20

Study of trench defects in green laser diodesAiqin Tian,*^{1,2} Jianping Liu,^{1,2} Renlin Zhou,^{1,2} Liqun Zhang,^{1,2} Siyi Huang,^{1,2} Wei Zhou,^{1,2} Masao Ikeda,^{1,2} Shuming Zhang,^{1,2} Deyao Li,^{1,2} Lingrong Jiang,^{1,2} and Hui Yang^{1,2}¹*Suzhou Institute of Nano-tech and Nano-bionics, Chinese Academy of Sciences, China,* ²*Key Laboratory of Nanodevices and Applications, Chinese Academy of Sciences, China*

ThP-OD-7 (Poster)

12:30 - 14:20

Study on the size dependent radiative recombination of GaN-based flip-chip micro light-emitting-diodes

Tae Kyoung Kim,* Abu Bashar Mohammad Hamidul Islam, Moon Uk Cho, Yu-Jung Cha, Jae Hyeok Lee, Jae Min Lee, Cheol Jeong, and Joon Seop Kwak

sunchon national university, Republic of Korea

ThP-OD-8 (Poster)

12:30 - 14:20

Conformational change from V_{Ga} to $\text{N}_{\text{Ga}}\text{-V}_{\text{N}}$ complex in GaN

Taishi Kakihara and Masato Oda*

Department of Applied Physics, Wakayama University, Japan

ThP-OD-9 (Poster)

12:30 - 14:20

Low threshold and high efficiency GaN-based blue laser diodes with ITO cladding layersLei Hu,*^{1,2} Xiaoyu Ren,² Jianping Liu,^{1,2} Aiqin Tian,² Liqun Zhang,^{1,2} and Hui Yang^{1,2}¹*School of Nano Technology and Nano Bionics, USTC, China,* ²*Suzhou Institute of Nano-Tech and Nano-Bionics, CAS, China*

ThP-OD-10 (Poster)

12:30 - 14:20

Investigation of the output power of green light-emitting diodes as functions of chip and V-pit sizesDa Hoon Lee,*¹ Daesung Kang,² Sang-Youl Lee,² Hyeong-Seop Im,³ Tae-Yeon Seong,^{1,3} and Hiroshi Amano⁴¹Department of Nanophotonics, Korea University, Seoul 02841, Republic of Korea, ²LED Division, LG Innotek Co., Ltd., Paju, Gyeonggi 10842, Republic of Korea, ³Department of Materials Science and Engineering, Korea University, Seoul 02841, Republic of Korea, ⁴Center for Integrated Research of Future Electronics, and Institute of Materials and Systems for Sustainability, Nagoya University, Nagoya 464-8603, Japan*ThP-OD-11 (No Show)*

12:30 - 14:20

Modified III-nitrides Nanostructures for Next-generation Energy HarvestersPraveen KUMAR*¹ and Pooja Devi²¹Indian Association for the Cultivation of Science-Kolkata, India, ²CSIR-Central Scientific Instruments Organisation, Chandigarh, India*ThP-OD-12 (Poster)*

12:30 - 14:20

AlN tunneling layer enhanced photo-detection in graphene heterojunction photodetectors

Lian Liu, Jun Yin,* Jing Li, and Junyong Kang

Xiamen University, China

ThP-OD-13 (Poster)

12:30 - 14:20

Experimental Study on Semipolar ($\bar{1}\bar{1}2\bar{2}$) LEDs toward Polar-Plane-Free Faceted InGaN LEDs on ($\bar{1}\bar{1}2\bar{2}$)

Yoshinobu Matsuda,* Mitsuru Funato, and Yoichi Kawakami

Kyoto University, Japan

ThP-OD-14 (Poster)

12:30 - 14:20

Development of GaN Waveguide Wavelength Filter for Quantum Optical ApplicationTenta Komatsu,*¹ Masafumi Kihira,¹ Toshiki Hikosaka,² Shinya Nunoue,² Masahiro Uemukai,¹ Tomoyuki Tanikawa,¹ and Ryuji Katayama¹¹Graduate School of Engineering, Osaka University, Japan, ²Corporate R&D Center, Toshiba Corporation, Japan*ThP-OD-15 (No Show)*

12:30 - 14:20

Dual-functioning subwavelength vertical-structure LED

Kang Fu,* Xumin Gao, Jialei Yuan, Linning Wang, Xinyu Xu, and Yongjin Wang

College of Telecommunications and Information Engineering, Nanjing University of Posts and Telecommunications, China

ThP-OD-16 (Poster)

12:30 - 14:20

Improving performance of GaN-based ultraviolet LEDs with Double ITO layers

Xiaomeng Fan* and Shengrui Xu

Wide Band-Gap Semiconductor Technology Disciplines State Key Laboratory, Xi'dian University, China

ThP-OD-17 (Poster)

12:30 - 14:20

Effect of Very High-Fluence Proton Radiation on 40 mm² 6H-SiC Photoconductive Proton DetectorsQing Liu,*¹ Dong Zhou,¹ Weizong Xu,¹ Ming Qi,² Dunjun Chen,¹ Fangfang Ren,¹ Rong Zhang,¹ Youdou Zheng,¹ and Hai Lu¹¹School of Electronic Science and Engineering, Nanjing University, China, ²School of Physics, Nanjing University, China*ThP-OD-18 (Poster)*

12:30 - 14:20

Effect of DEZn flow rate modulation to phototransistors based on ZnGa₂O₄ epilayers grown by MOCVD

PENG HSUAN HUANG,* YUAN CHU SHEN, CHIUNG YI HUANG, and RAY HUA HONG

Institute of Electronics Engineering, National Chiao Tung University, Taiwan

ThP-OD-19 (Poster)

12:30 - 14:20

Successive Formation of Metal Oxide and Cesium Lead Halide Perovskites Thin Films Using a Mist Deposition Method for All-Inorganic Perovskite Solar Cells

Yuki Haruta,* Takumi Ikenoue, Masao Miyake, and Tetsuji Hirato
Graduate School of Energy Science, Kyoto University, Japan

ThP-OD-20 (Poster)

12:30 - 14:20

Enhancement-mode Light Emitting AlGaIn/GaN HEMT

Chih-Yao Chang,* Shao-Hsiang Huang, and Chih-Fang Huang
Institute of Electronics Engineering, National Tsing Hua University, Taiwan

ThP-OD-21 (Poster)

12:30 - 14:20

Optimization of p-Cladding Layer for Improvement of Deep Ultraviolet Light Emitting Diode performance

Yuji Tomita,*¹ Akira Mishima,² Yuya Yamaoka,¹ Tadanobu Arimura,¹ Shuuichi Koseki,¹ Yoshiki Yano,¹ Kou Matsumoto,¹ and Hideki Hirayama³
¹Taiyo Nippon Sanso Corporation, Japan, ²TNCSE, Japan, ³RIKEN, Japan

ThP-ED-1 (Poster)

12:30 - 14:20

Reduction of Self-Heating in GaN HEMT with Micro-Trench Structure on Silicon Substrate

Srikant Kumar Mohanty and Ray Hua Horng*
Institute of Electronics, National Chiao Tung University, Taiwan

ThP-ED-3 (Poster)

12:30 - 14:20

Stability of all-solid-state AlGaIn/GaN based pH sensors integrated a quasi-reference electrode

Jieying Xing,¹ Yaqiong Dai,*¹ Deji Huang,¹ Yuebo Liu,¹ Yuan Ren,¹ Xiaobiao Han,¹ Zhisheng Wu,² Yang Liu,^{1,2} and Baijun Zhang^{1,2}
¹School of Electronics and Information Technology, Sun Yat-sen University, China, ²State Key Laboratory of Optoelectronic Materials and Technologies, Sun Yat-sen University, China

ThP-ED-4 (Poster)

12:30 - 14:20

Simulation Design of GaN Vertical Junction Barrier Schottky Diode with High-K/Low-K Compound Dielectric Structure

Kuiyuan Tian, Jiangfeng Du,* Qi Xin, Yong Liu, and Qi Yu
State Key Laboratory of Electronic Thin Films and Integrated Devices, University of Electronic Science and Technology of China, China

ThP-ED-5 (Poster)

12:30 - 14:20

Effects of Long-Term Low-Temperature Annealing on Mg-Ion Implanted GaN

Shunta Murai,* Ryo Kamoshida, and Masamichi Akazawa
Hokkaido University, Japan

ThP-ED-6 (Poster)

12:30 - 14:20

Design of an L Band GaN Power Amplifier Based on the Transconductance Modified Model

Ziyue Zhao,*^{1,3} Yang Lu,^{2,3} Hengshuang Zhang,^{2,3} Chupeng Yi,^{1,3} Yuchen Wang,^{1,3} Xiaohua Ma,^{2,3} and Yue Hao^{2,3}
¹School of Advanced Materials and Nanotechnology, Xidian University, China, ²School of Microelectronics, Xidian University, China, ³Key Laboratory for Wide Band-Gap Semiconductor Materials and Devices, Xidian University, China

ThP-ED-8 (No Show)

12:30 - 14:20

An enhancement mode MOSFET on GaN-on-silicon for monolithic OEIC

Jiabin Yan,* Jinlong Piao, and Yongjin Wang
Peter Grunberg Research Center, Nanjing University of Posts and Telecommunications, China

ThP-ED-9 (Poster)

12:30 - 14:20

Trapping and temperature effect on performance of GaN vertical nanowire transistor

Terirama Thingujam,* Dong-Hyeok Son, Woo-Hyun Ahn, and Jung-Hee Lee
School of Electronics Engineering, Kyungpook National University, Republic of Korea

ThP-ED-10 (Poster)

12:30 - 14:20

Highly enhanced gate stability in p-GaN gate HEMTs with post-annealing process catalyzed by Ni gate metal

Changkun Zeng,* Weizong Xu, Fangfang Ren, Dong Zhou, Dunjun Chen, Rong Zhang, Youdou Zheng, and Hai Lu
School of Electronic Science and Engineering, Nanjing University, China

ThP-ED-11 (Poster)

12:30 - 14:20

Temperature effects of pre-passivation on P-GaN gated AlGaIn/GaN HEMT

Won-Ho Jang,* Hyun-Seop Kim, Dac Duc Chu, Hyungtak Kim, Ho-Kyoung Lee, Hyunsik Shin, and Ho-Young Cha
School of Electronic and Electrical Engineering, Hongik University, Republic of Korea

ThP-ED-12 (Poster)

12:30 - 14:20

Degradation analysis of SiN_x/GaN MIS-HEMTs under negative gate voltage and drain voltage stress

Tao tao Que,*¹ Ya wen Zhao,¹ Liu an Li,¹ Zhen xing Liu,¹ Jin wei Zhang,¹ Xin Gu,¹ Liang He,¹ and Yang Liu^{1,2}
¹*School of Electronics and Information Technology, Sun Yat-Sen University, China,* ²*State Key Laboratory of Optoelectronic Materials and Technologies, Sun Yat-sen University, China*

ThP-ED-13 (Poster)

12:30 - 14:20

Performance of NO₂ gas sensor based on Pd-AlGaIn/GaN HEMT at high temperatures

Cuong Van Nguyen,* Anh Tuan Vuong, Dongmin Keum, and Hyungtak Kim
School of electronic and electrical engineering, Hongik University, Republic of Korea

ThP-ED-14 (Poster)

12:30 - 14:20

Impact Ionization Coefficients for 4H-SiC on a-face (11-20) and their Temperature Variations

Dionysios Stefanakis,* Xilun Chi, Takuya Maeda, Mitsuaki Kaneko, and Tsunenobu Kimoto
Dept. of Electronic Sci. & Eng., Kyoto University, Japan

ThP-ED-16 (Poster)

12:30 - 14:20

Recessed β -Ga₂O₃ Schottky barrier diode

June-Heang Choi* and Ho-Young Cha
School of Electronic and Electrical Engineering, Hongik University, Seoul, Republic of Korea

ThP-ED-17 (Poster)

12:30 - 14:20

Electrical characteristics of Gallium dopant-induced reduced graphene oxide/GaN Schottky diodes

Beo Deul Ryu,* Min Han, Kang Bok Ko, Gun Hee Lee, and Chang-Hee Hong
Chonbuk National University, Republic of Korea

Plenary 3

Auditorium 14:30-15:20

Chair: Hideki Hirayama

PL-5 (Plenary)

14:30 - 15:20

Progress of halide perovskite semiconductors in high performance photovoltaics

Tsutomu Miyasaka

¹*Toin University of Yokohama, Japan,* ²*Peccell Technologies, Inc., Japan*

Closing

Auditorium 15:20-15:50